



Photonique sur silicium : une nouvelle plateforme d'intégration photonique

Guang-Hua DUAN

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**III-V Lab, a joint lab of 'Alcatel-Lucent Bell Labs France',
'Thales Research and Technology' and 'CEA Leti',
Campus Polytechnique, 1, Avenue A. Fresnel, 91767
Palaiseau cedex, France.**

▶ **Motivation**

- Photonic integrated circuits on silicon for optical communications
- Comparison of InP PICs and silicon PICs

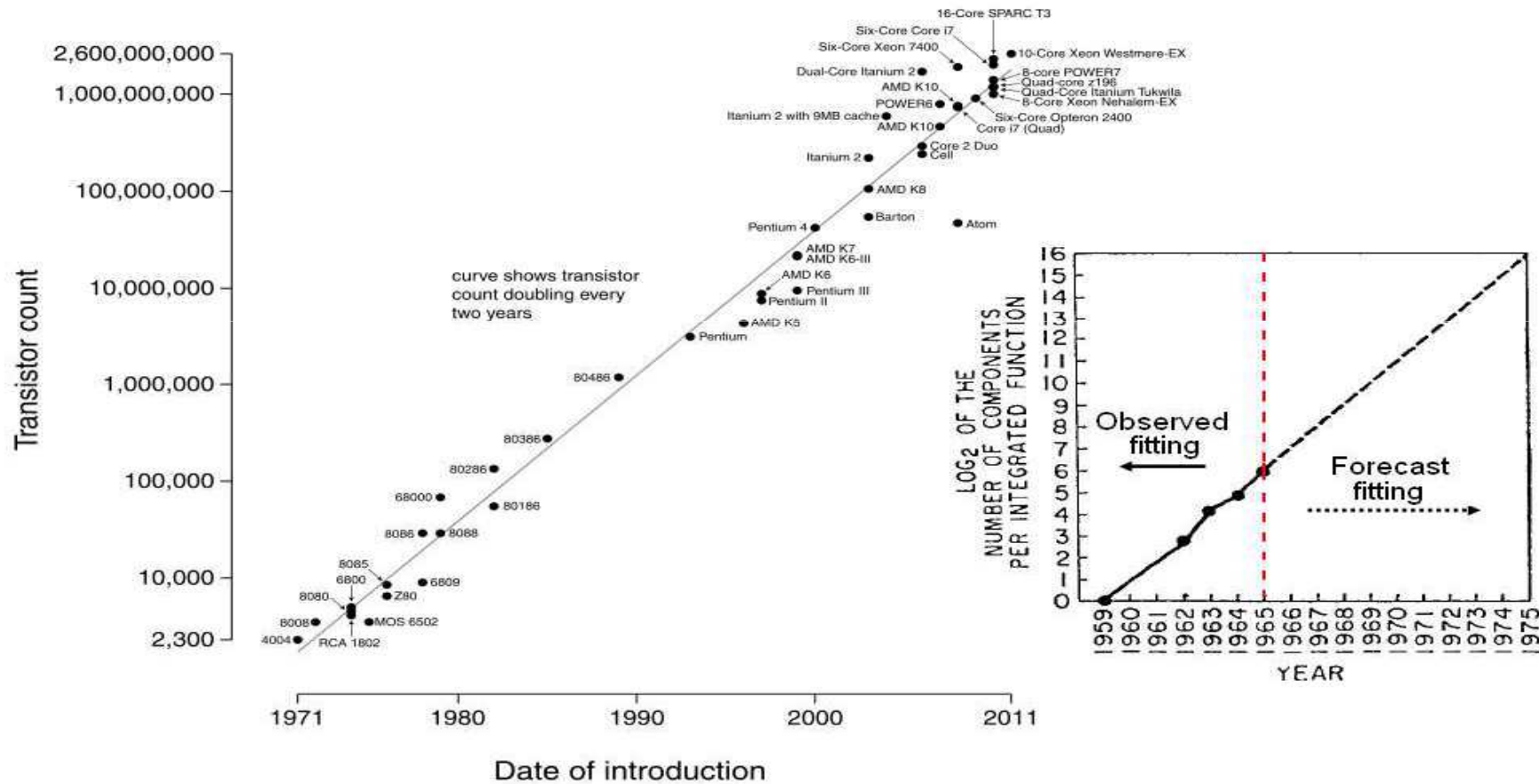
▶ **Current state of art of silicon photonics**

▶ **Hybrid III-V/Si integration technology**

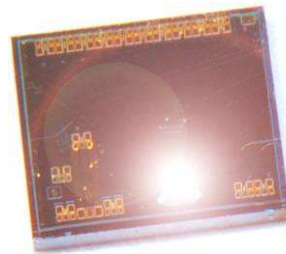
- Hybrid integration technology
- Hybrid III-V/Si lasers
- Integrated tunable laser- Mach-Zehnder modulator

▶ **Future directions**

Microprocessor Transistor Counts 1971-2011 & Moore's Law



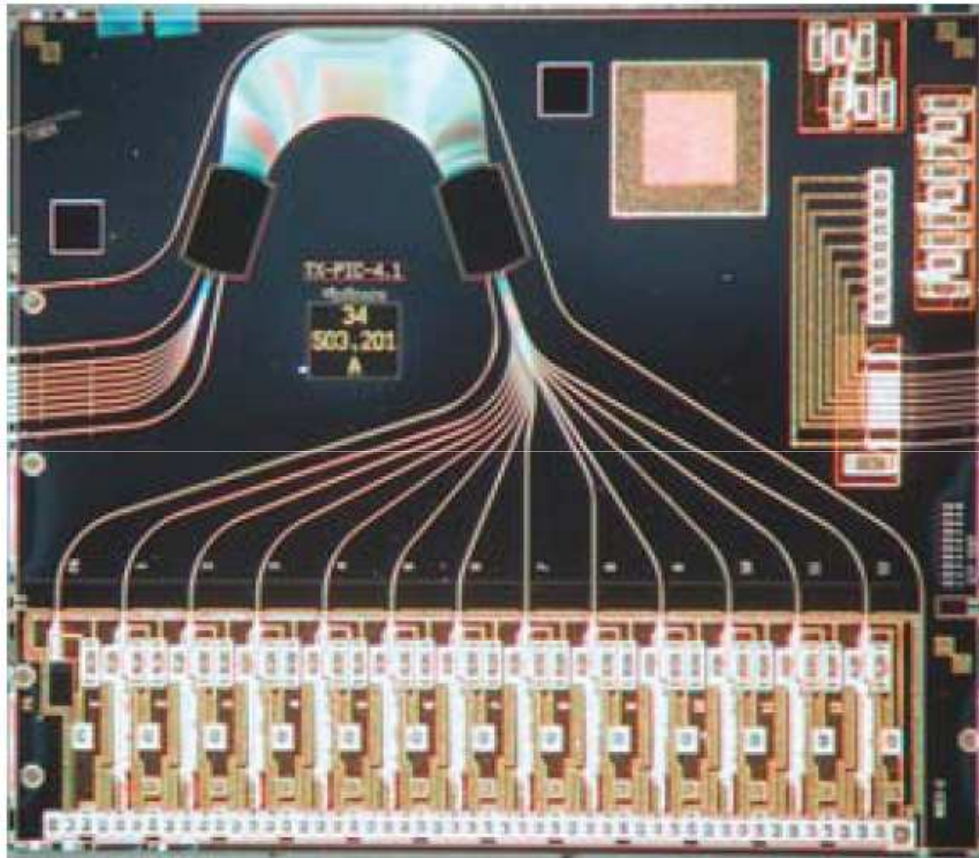
100Gb/s Receive



100Gb/s Transmit



Courtesy from Infinera



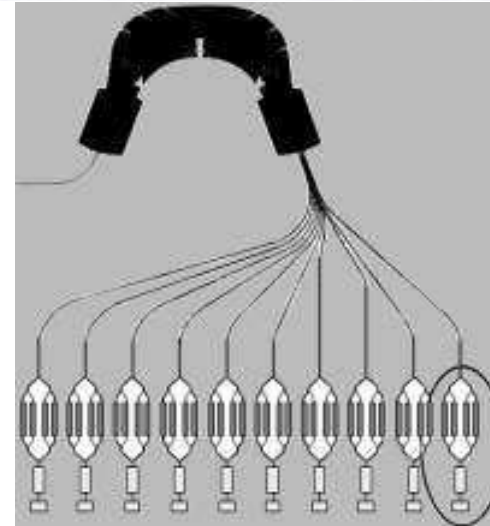
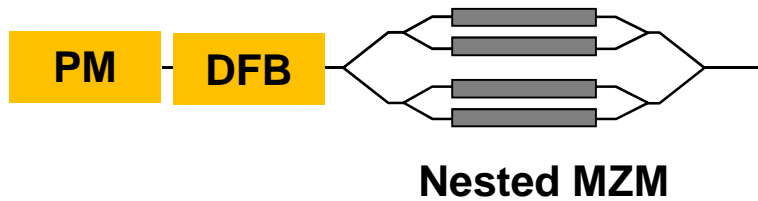
Photonic Integration

Small footprint

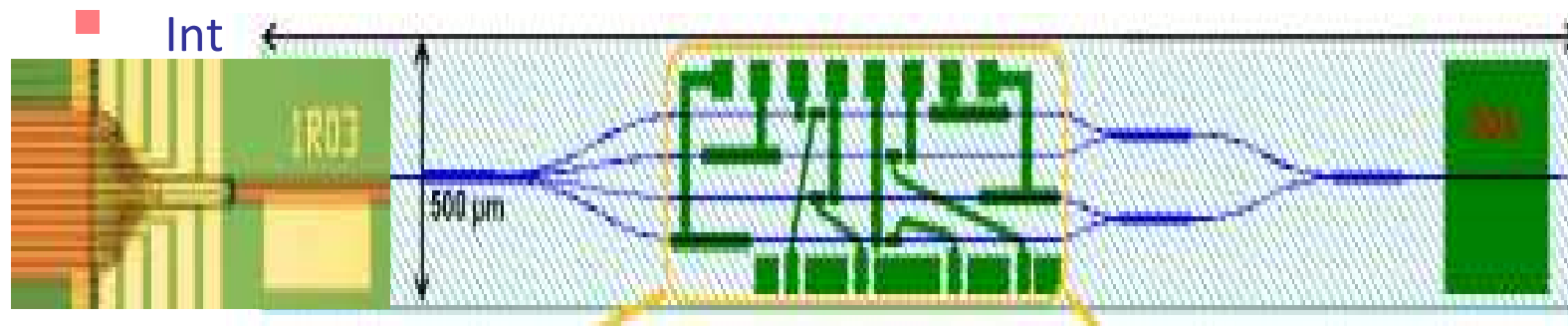
Cost effective

Reduced power consumption

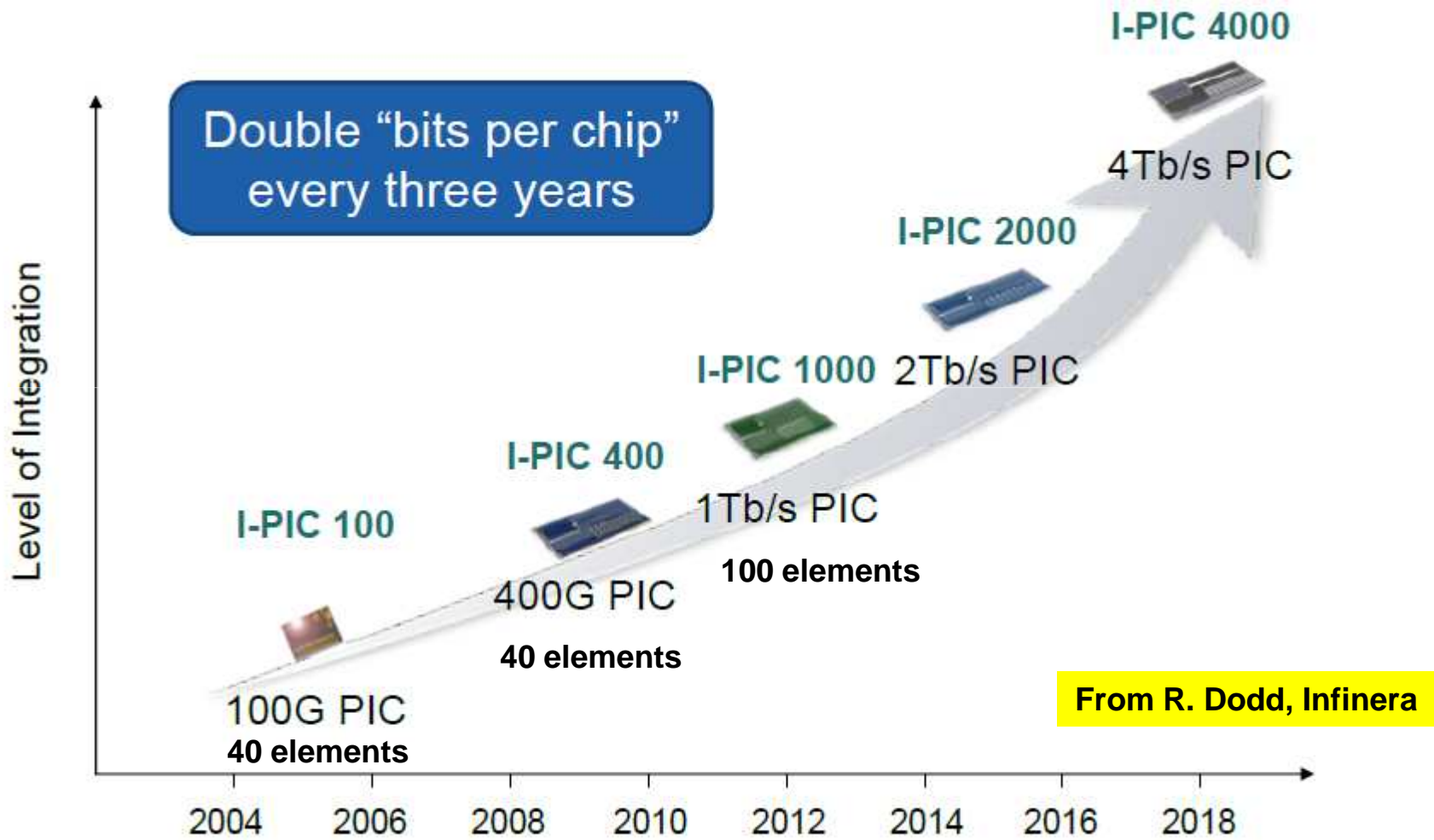
▶ **Infinera's QPSK transmitter:**



▶ **Bell Lab's QPSK/QAM Source**



I. Kang, Optics Express 2007



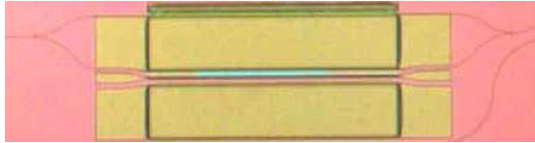
▶ **CMOS EIC platform on silicon**

- Mature industrial process with high yield
- Foundry model for cost-effective industrial production
- Cost-effective for large volume

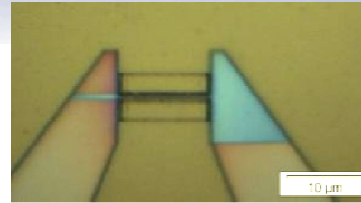
▶ **PICs on silicon**

- Taking benefit for EICs: industrial tools, foundry models, etc.
- Co-integration with CMOS electronics, close proximity between signal processing unit and photonic elements
- Providing optical interconnect solutions for “More than Moore” for EICs

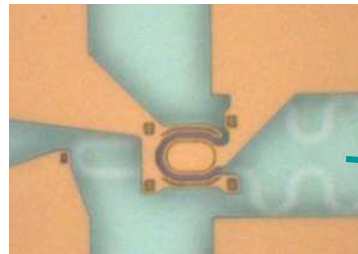
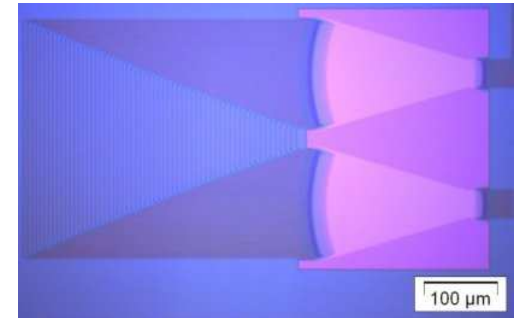
Can silicon be a Photonic integration platform?



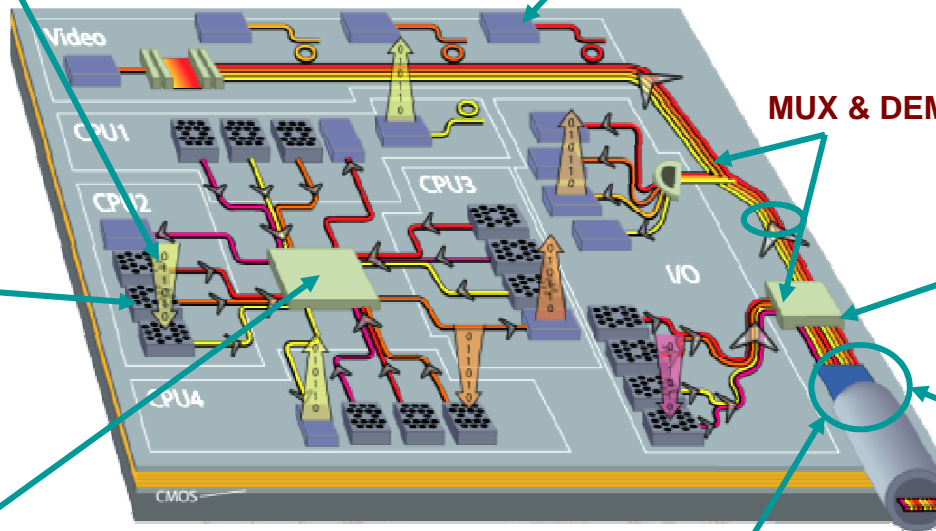
Optical modulator



Photodetector



Laser source



MUX & DEMUX

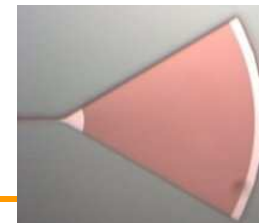


Waveguide



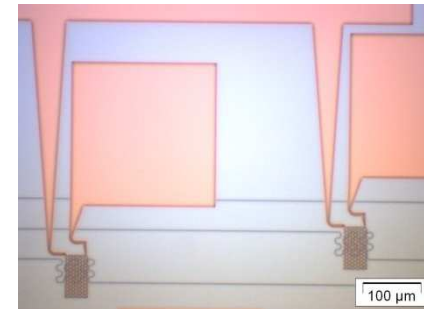
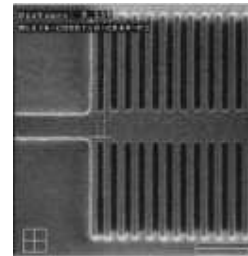
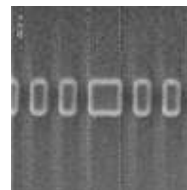
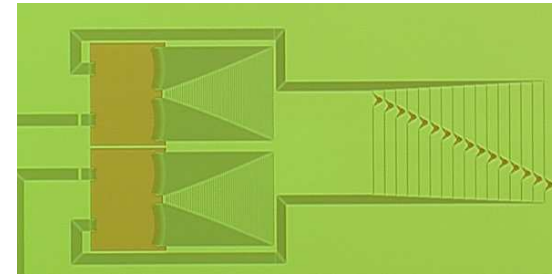
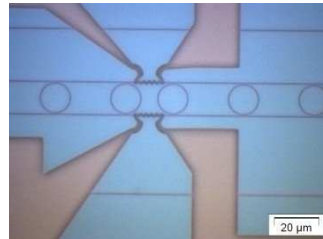
Optical switch

In-plane coupler

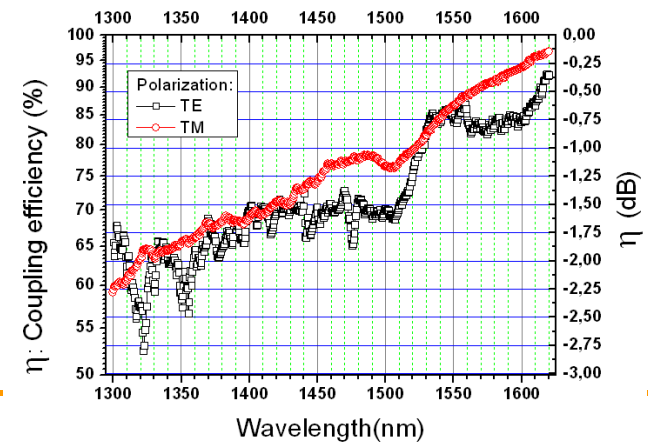


Grating coupler

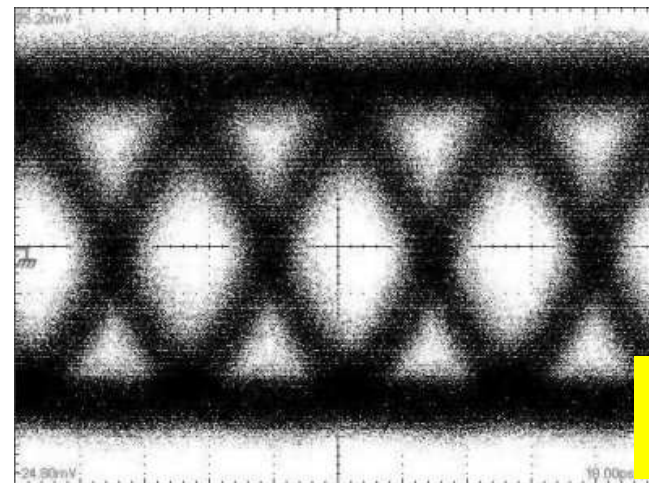
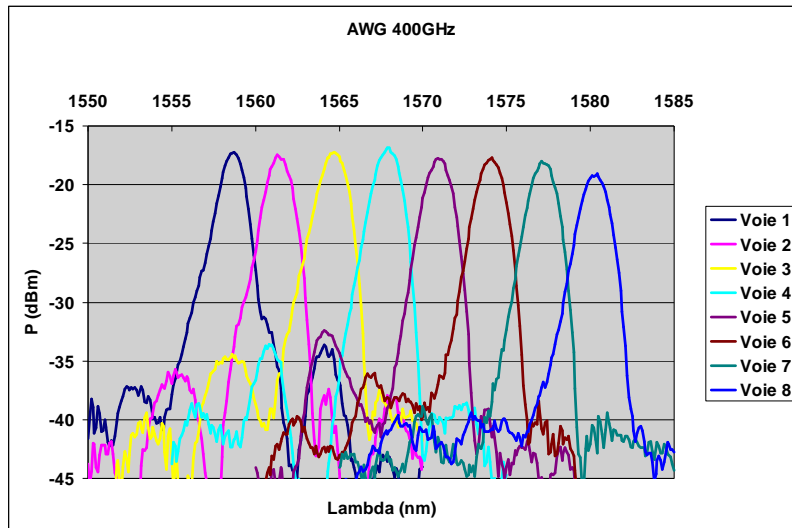
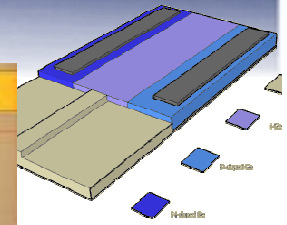
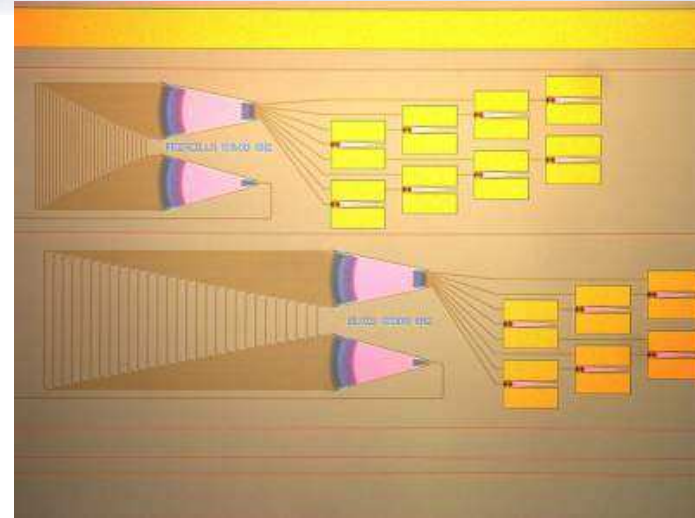
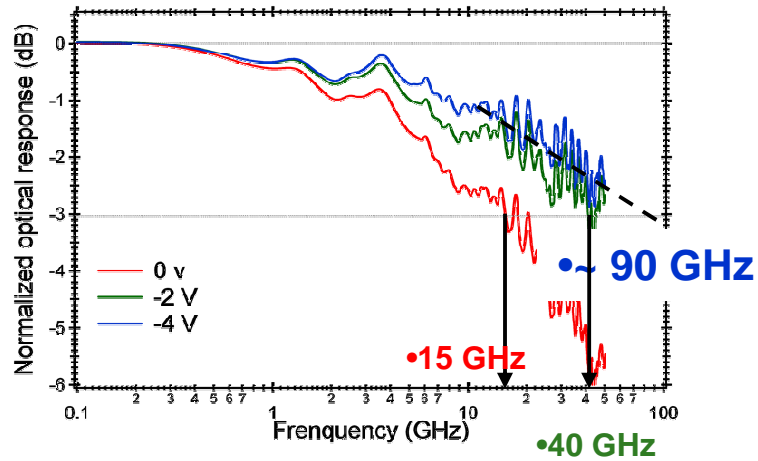
- Waveguides
- Transitions
- Splitters
- MMI
- Resonators
- AWG
- oNoC
- Slow wave structure



Edge coupling with inverted taper: <1dB losses



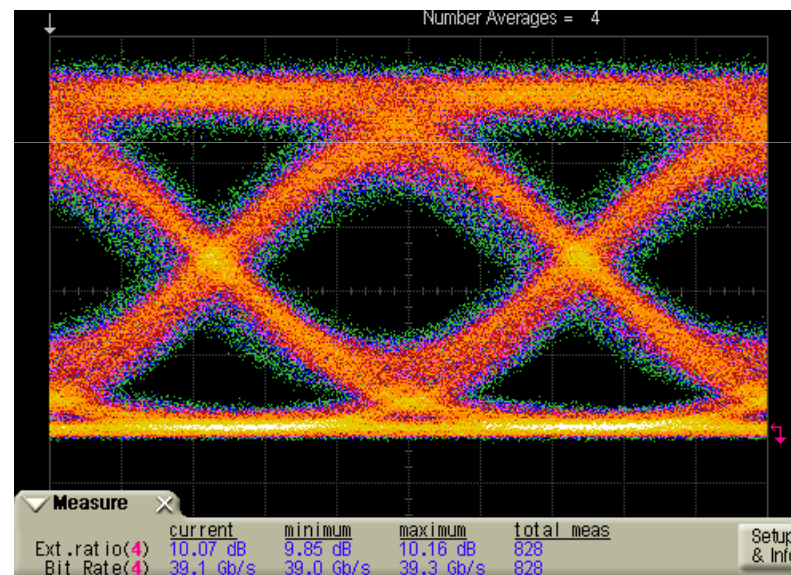
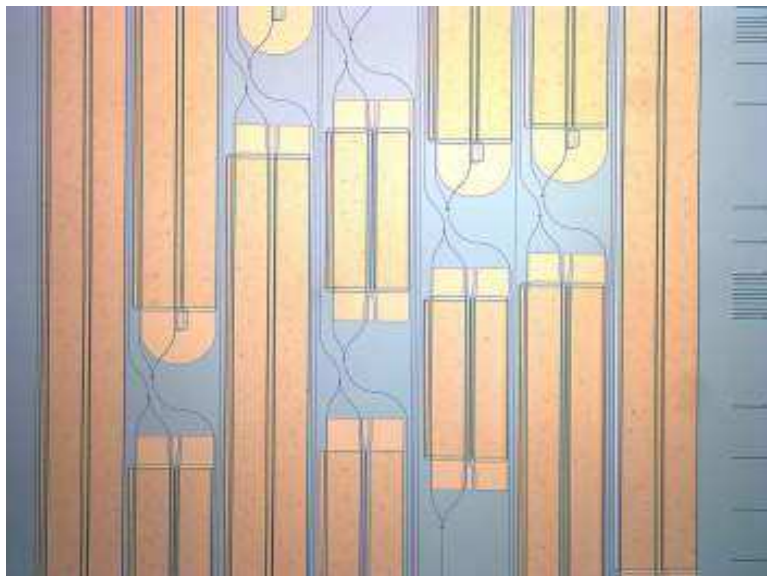
•Germanium photodetectors



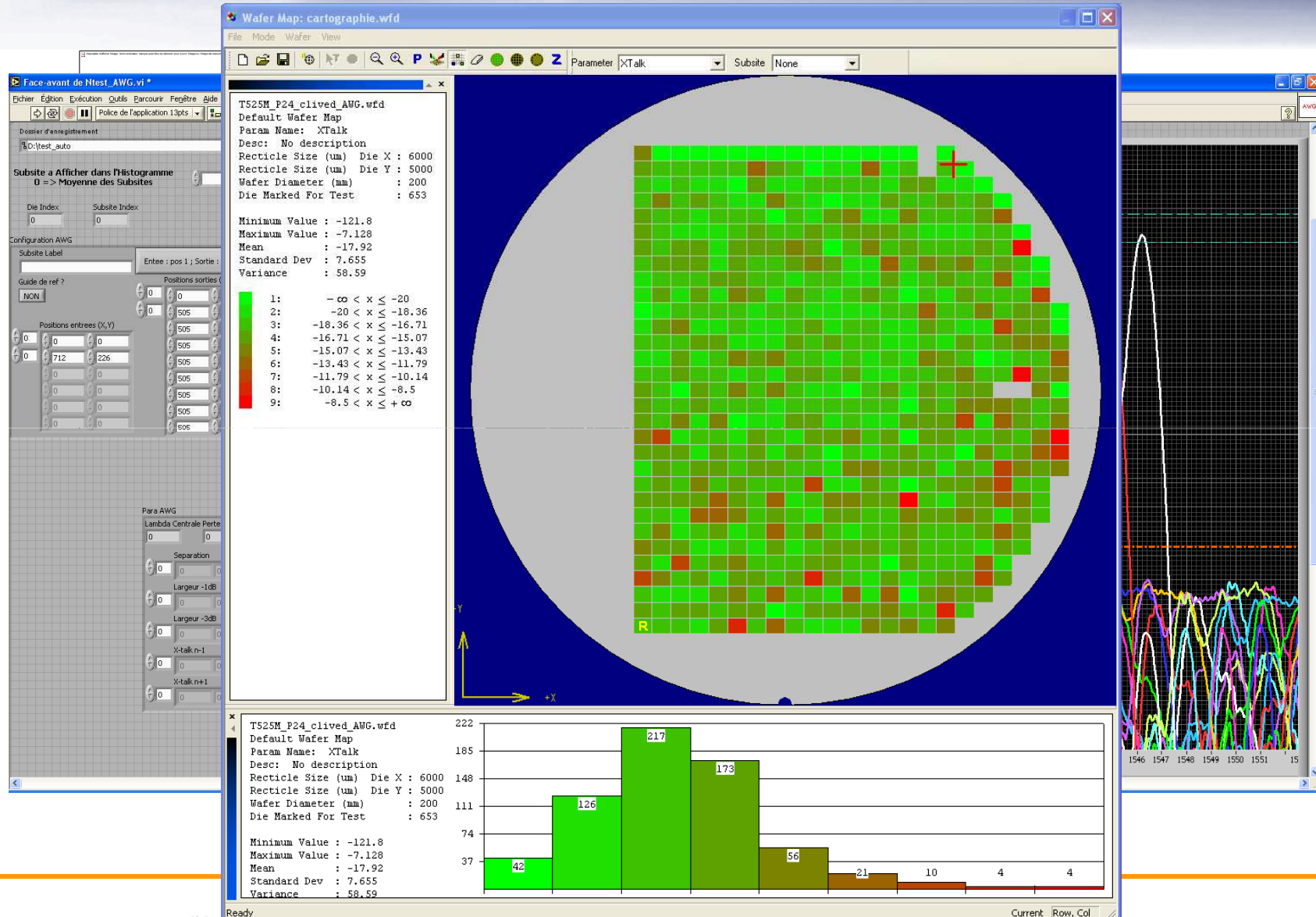
From L. Vivian, IEF

•Eye diagram @ 40Gbps

- ▶ 40Gb/s demonstrated with 10dB extinction ratio
- ▶ Tradeoff between losses, power consumption and extinction ratio



From D. Morris, IEF



	InP platform (III-V Lab)	Si-photonics platform (III-V Lab, CEA, LETI)
Functionality	Source, Detector, Waveguide, Modulator	Detector, Waveguide, Modulator Massive electronic integration No source: need for InP hetero-integration or Ge sources
Performance	Excellent optical performance No large scale integration with electronics	Good optical performance Large scale integration with electronics for 'free'
Footprint	Large for passive elements (AWG, ring resonators, etc)	Compact for passive elements (AWG, ring resonators, etc)
Cost	Higher due to individual device testing, Low yield for PICs	Wafer scale testing CMOS processing & monitoring for 'free' Foundry model for volume production will drive cost down
Power consumption	Low for electro-absorption modulator, higher for Mach-Zehnder type modulator	Novel modulator design results in low drive voltage

▶ Silicon photonics approach:

- Mature CMOS fabrication process
- Available key building blocks: modulators, detectors, low loss passive waveguides, wavelength multiplexers/demultiplexers
- Lack of efficient lasers sources on silicon

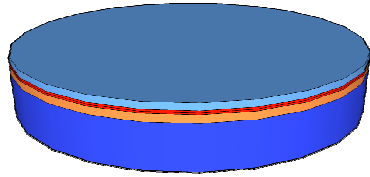
▶ Sources for silicon photonics

- Ge on silicon lasers and Epitaxy of III-V layers on silicon through a buffer layers: very promising results, but still requiring developments
- Hybrid III-V/Si integration using wafer bonding: most efficient solution today

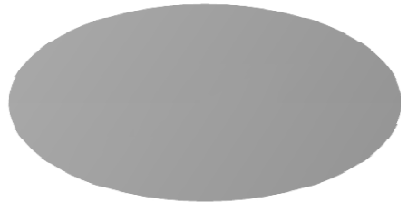
▶ Hybrid III-V/Si integration combining advantages of III-V and Si

- III-V: providing optical gain
- Si: providing wavelength selection and tuning using passive silicon waveguides
- Dies to wafer or wafer to wafer bonding proven to be a reliable process for SOI wafers
- => a new classe of tunable lasers with large tuning range, high SMSR and compact size
- => PIC transmitter integrating tunable lasers and silicon modulators

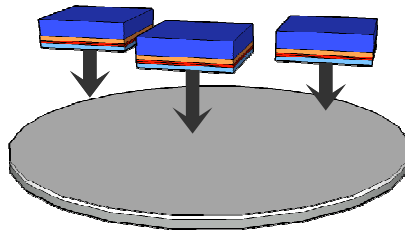
Growth of the III-V wafers



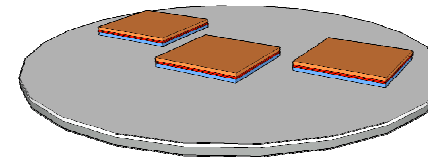
Processing of SOI wafers (modulators, detectors, passive waveguides, etc.)



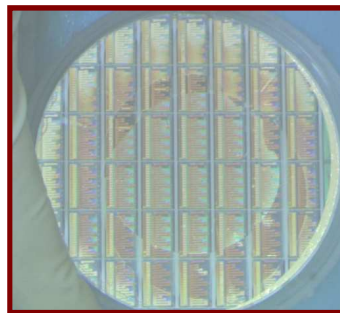
III-V die or wafer bonding on SOI (unprocessed)



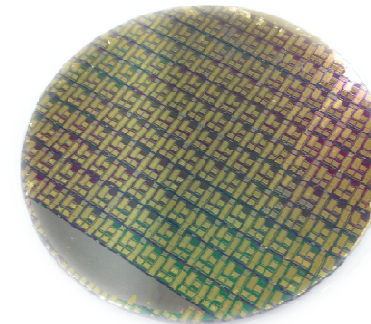
InP substrate removal



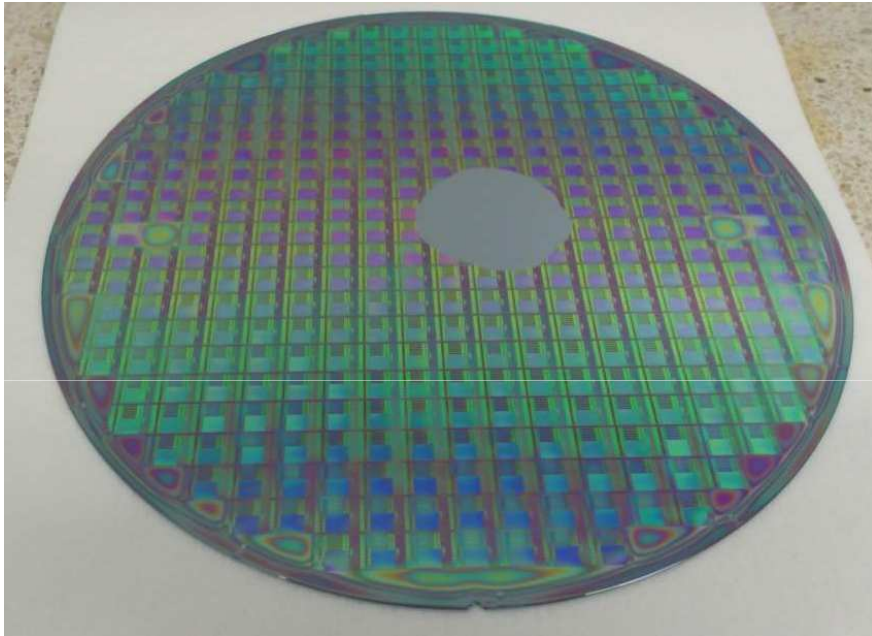
Processing of III-V dies/wafer



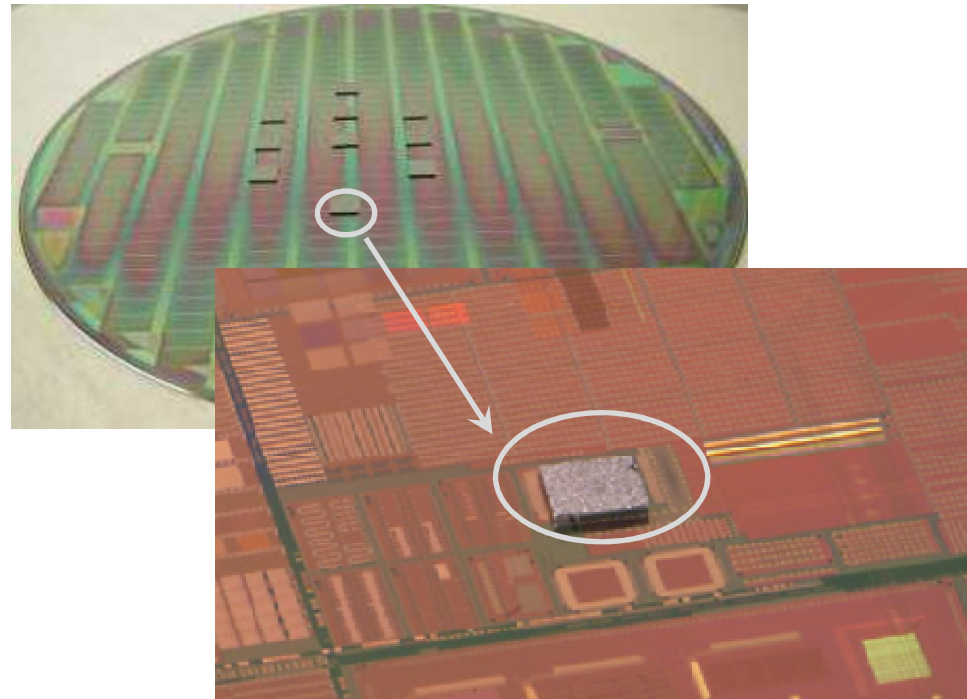
Metallization of lasers, modulators and detectors

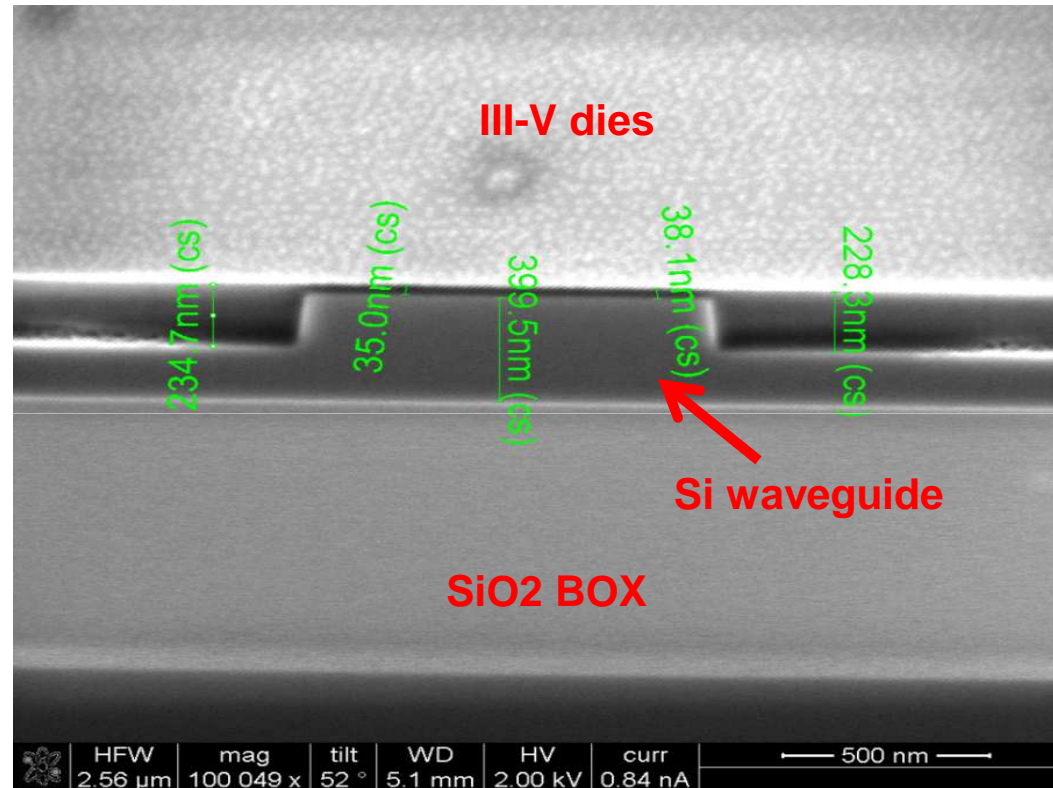


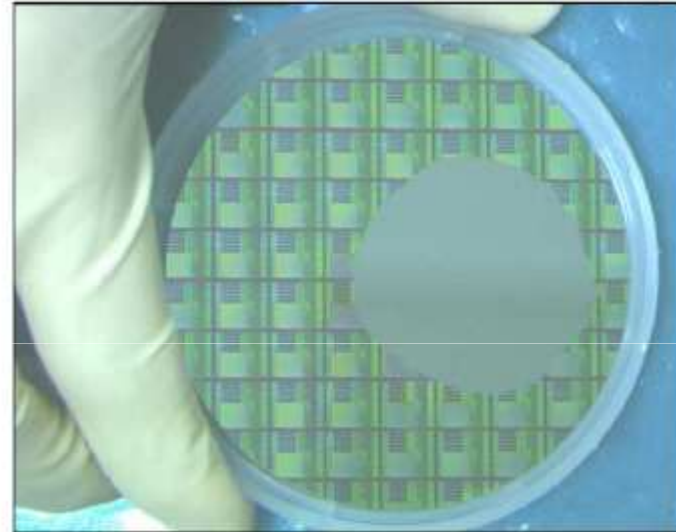
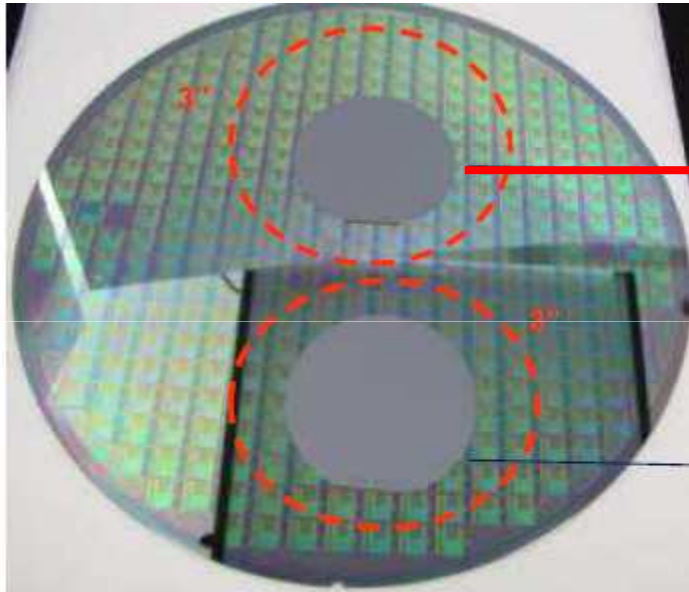
Wafer to wafer bonding



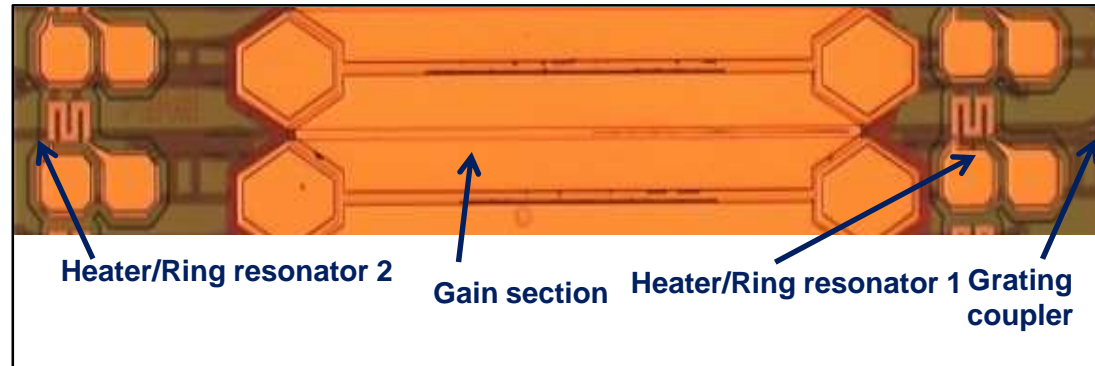
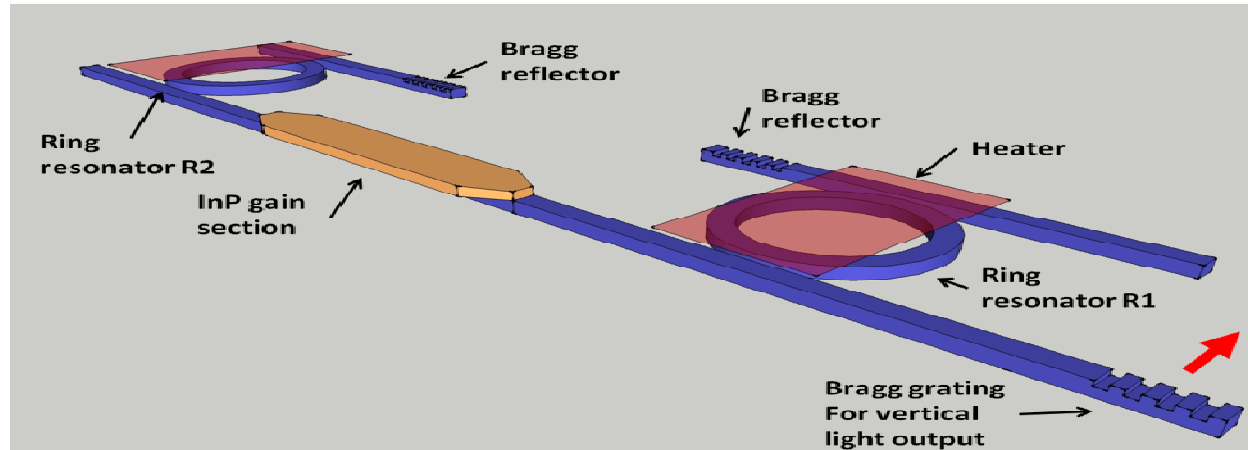
Dies to wafer bonding





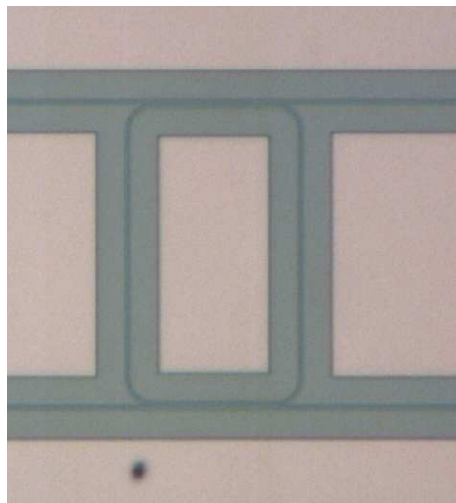


Laser cutting of 8" wafers into 3" wafers,
ready to be processed in a III-V foundry



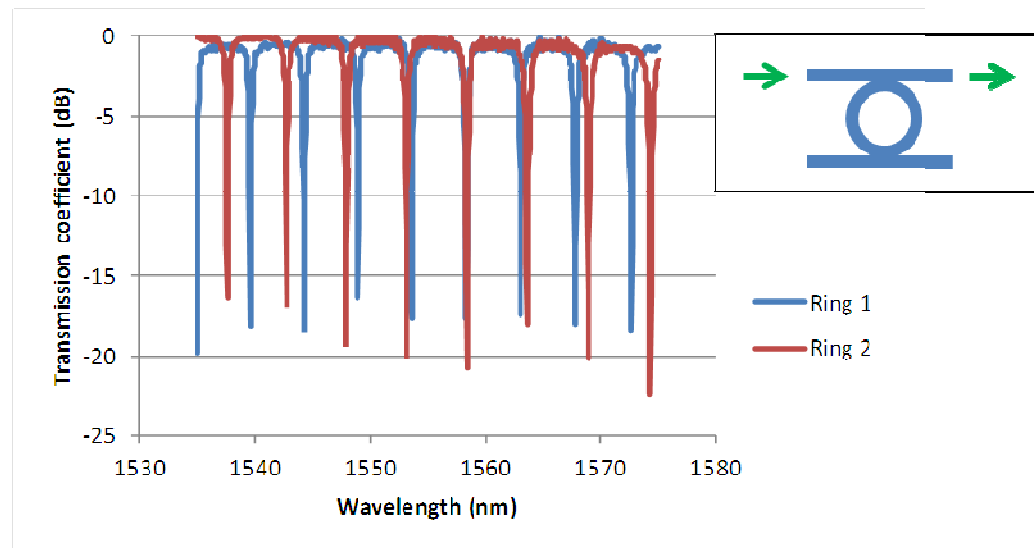
A. Le Liepvre, et al., GFP Conference, Aug. 2012

- ▶ **Low loss in waveguides and bends**
 - 90° Turn : 0.01 dB loss for 5 μ m radius
- ▶ **High finesse (> 10) ring/racetracks resonators in Si with FSR around 5nm**

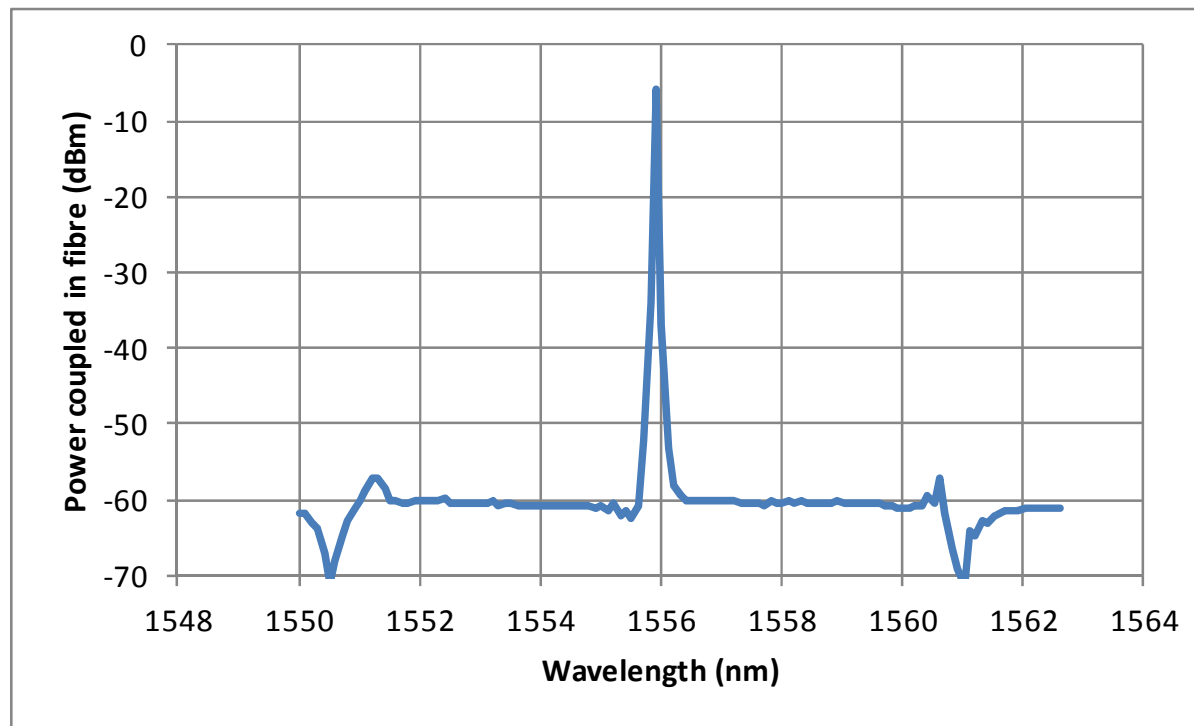


Si Racetrack resonator

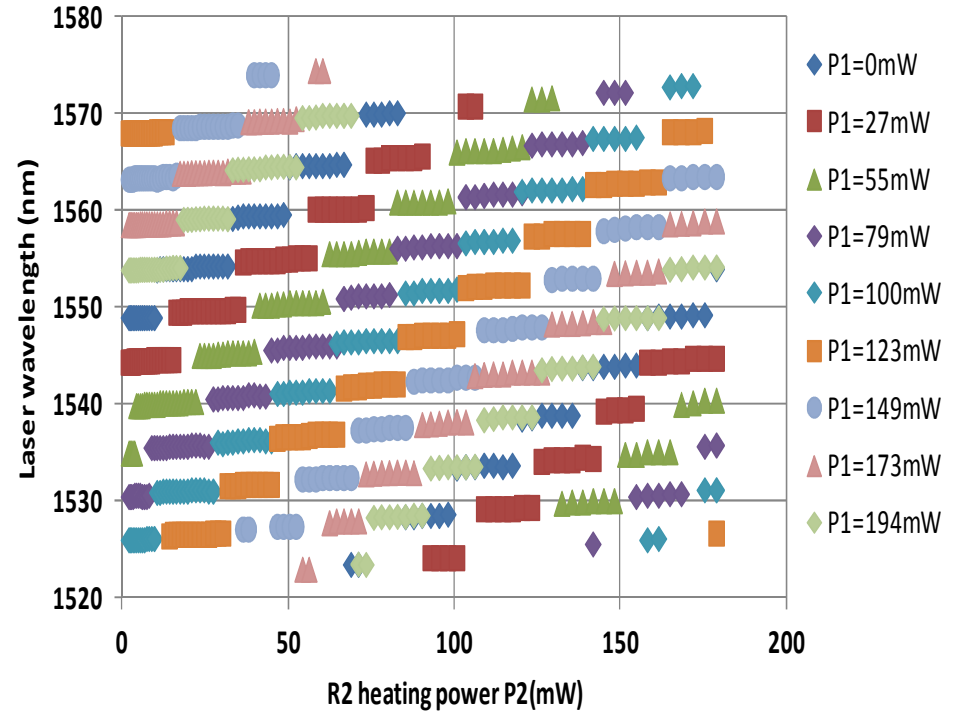
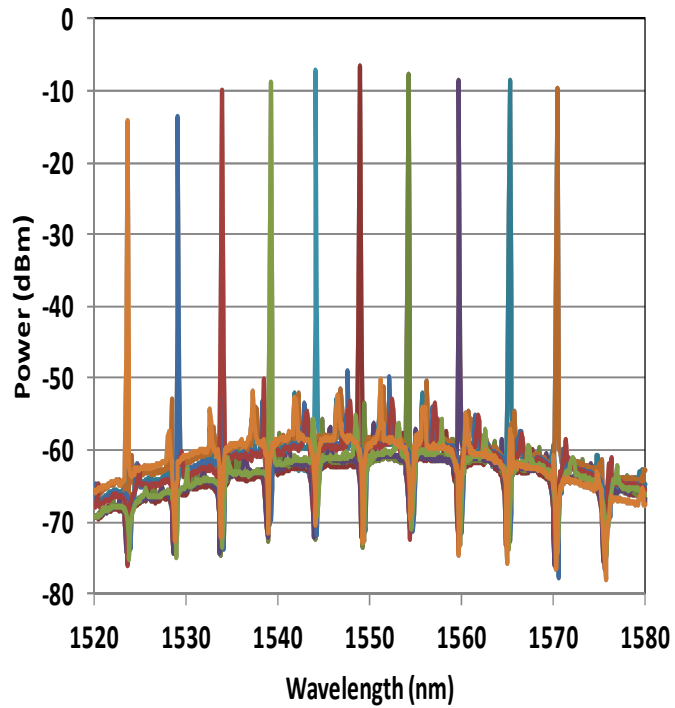
Measured transmission of two ring resonators used in the laser



- ▶ **Threshold : 22mA, maximum total output power 10 dBm**
- ▶ **Single-mode operation with SMSR > 40 dB**
- ▶ **Series resistance : 5-6 Ω**

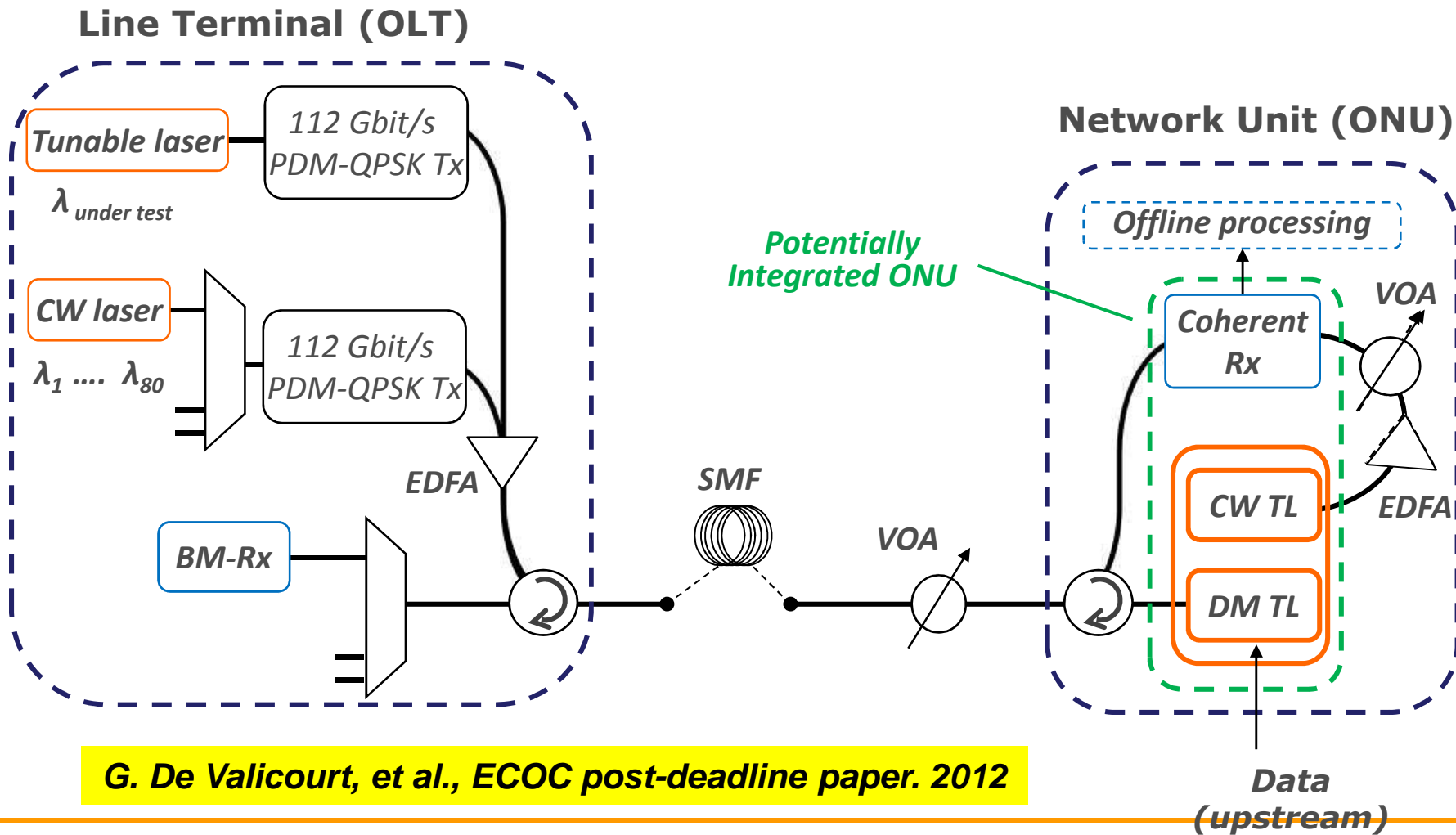


Laser spectrum for I=80mA, T=20°C

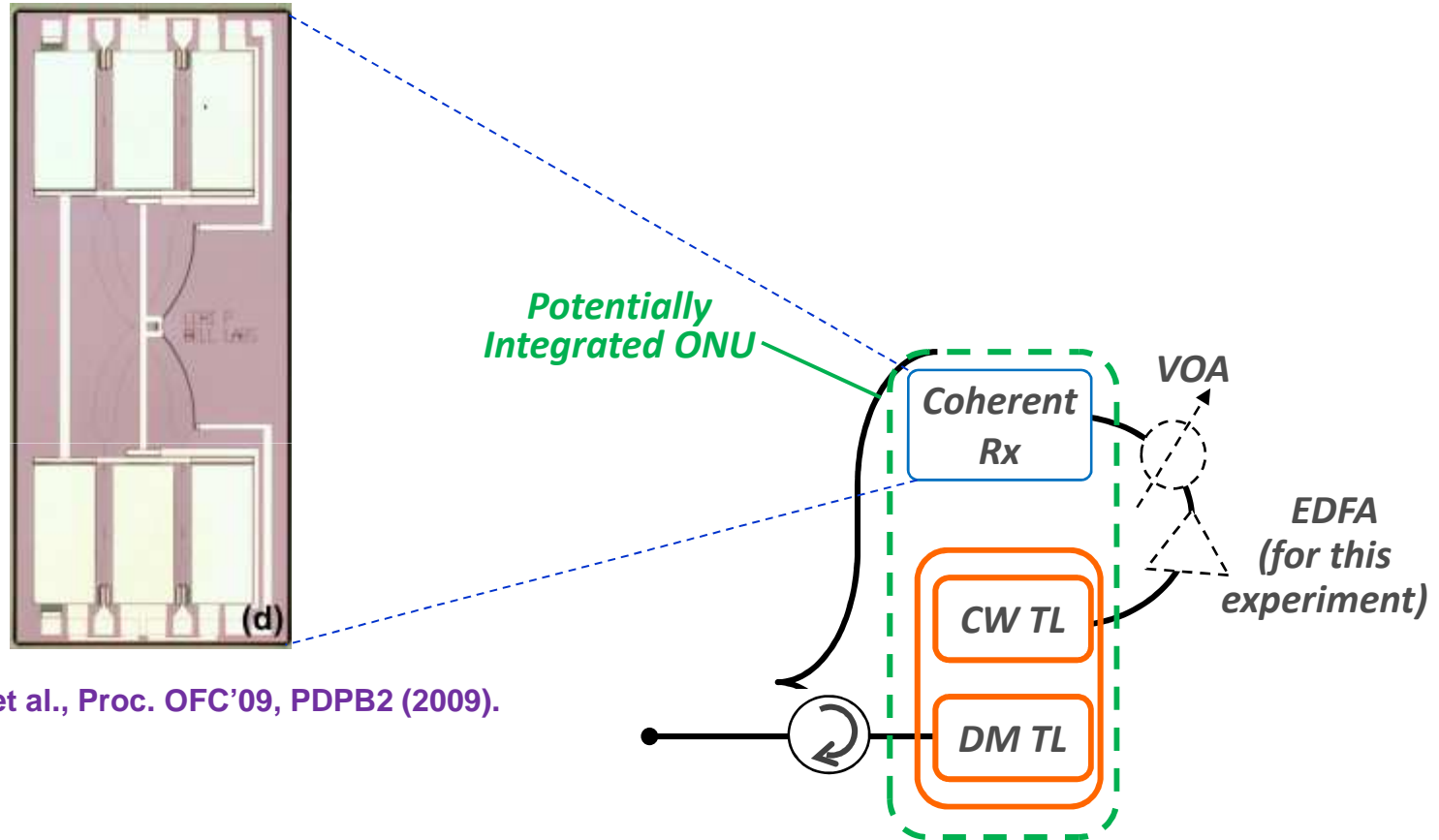


- 45 nm tuning range with SMSR > 40 dB over the tuning range
- More robust single mode operation than InP based tunable lasers

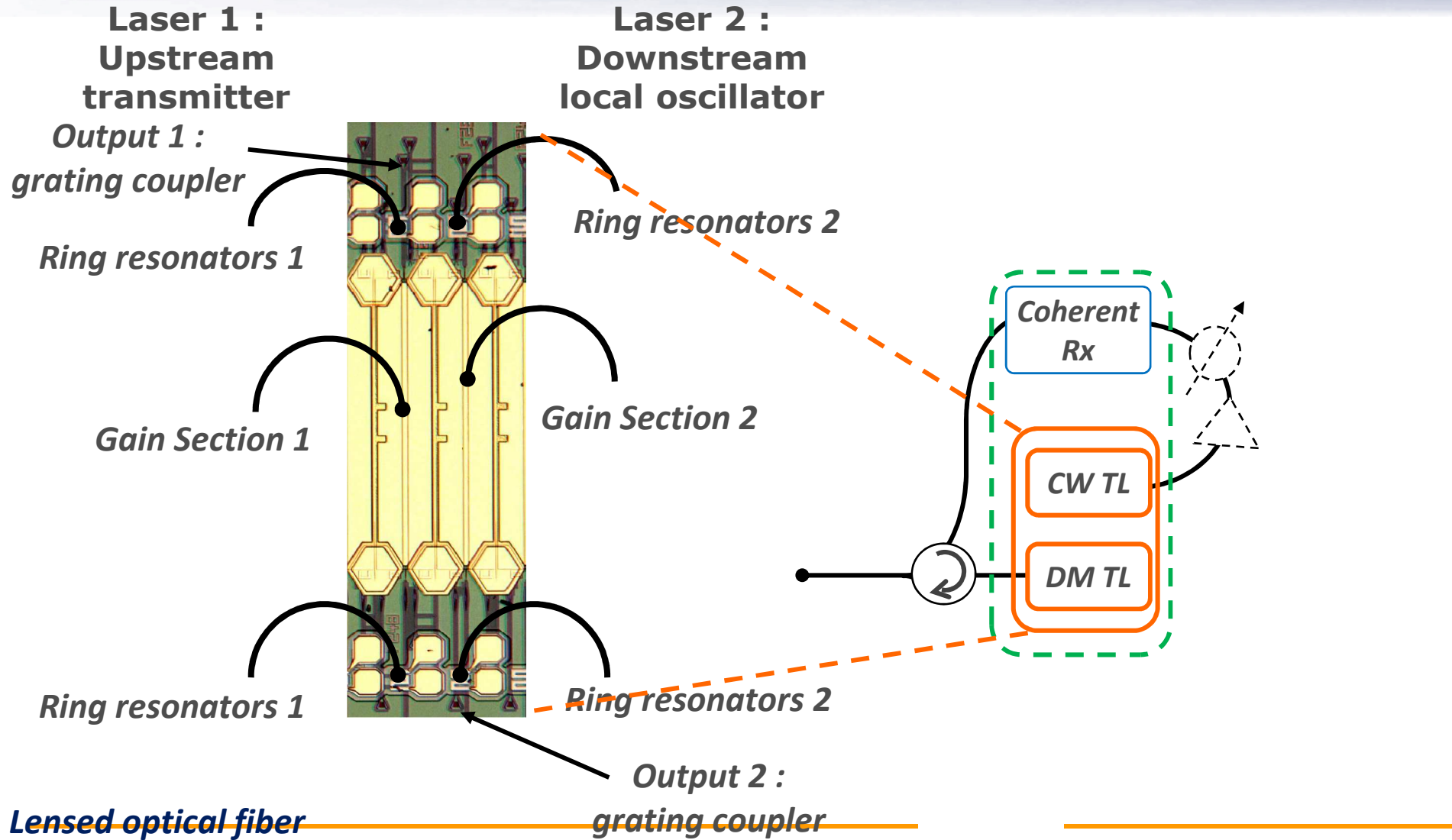
Tunable transmitter and local oscillator in a coherent receiver

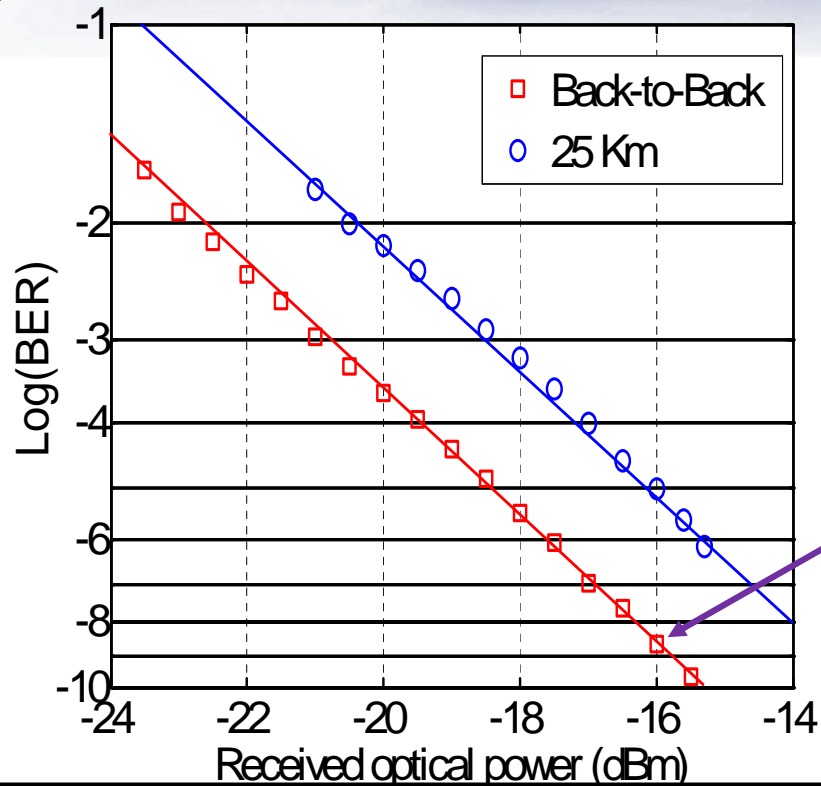


G. De Valicourt, et al., ECOC post-deadline paper. 2012

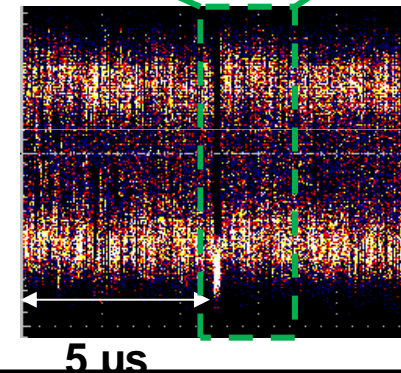
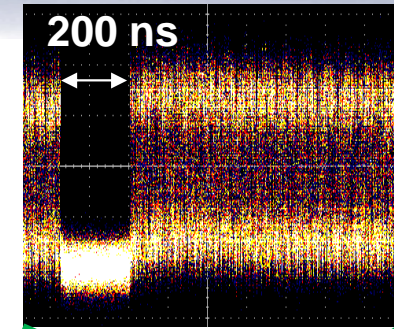
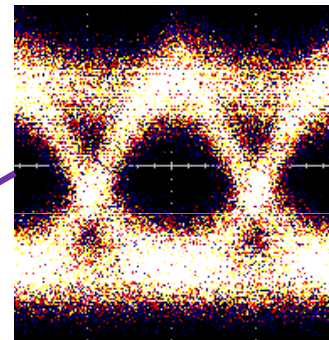


[1] C. R. Doerr et al., Proc. OFC'09, PDPB2 (2009).



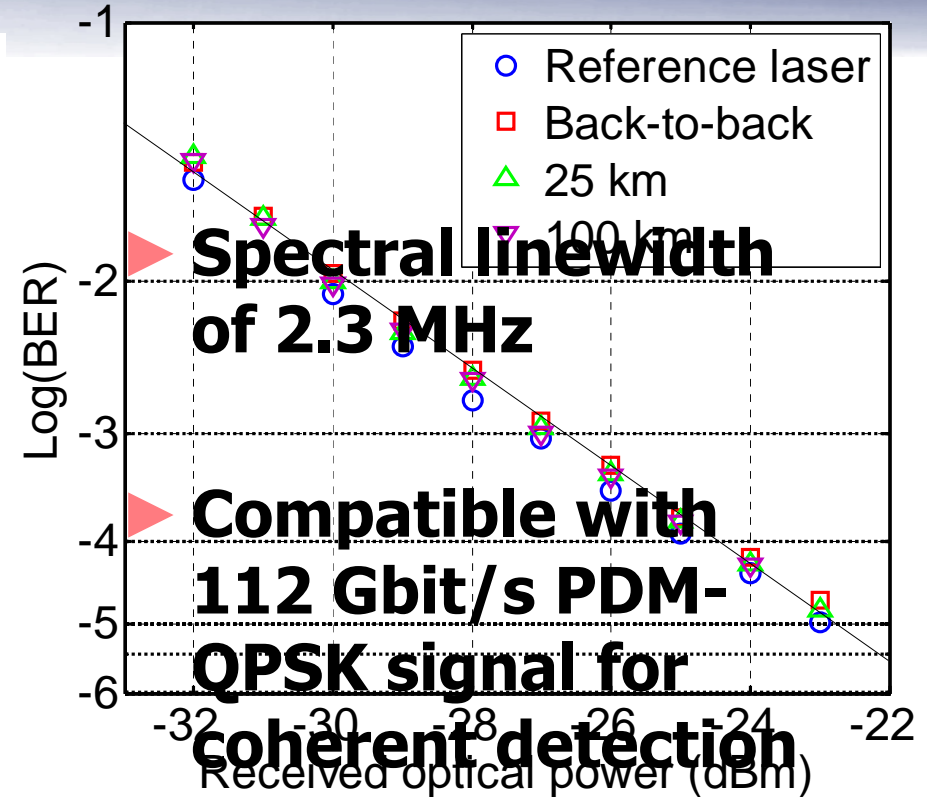
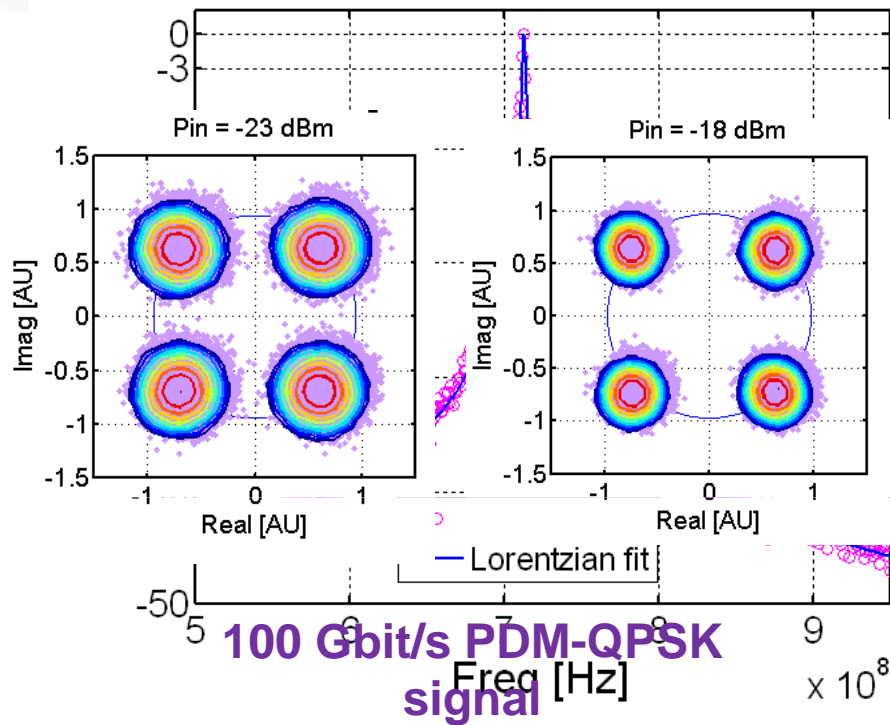


10 Gbit/s OOK burst mode operation

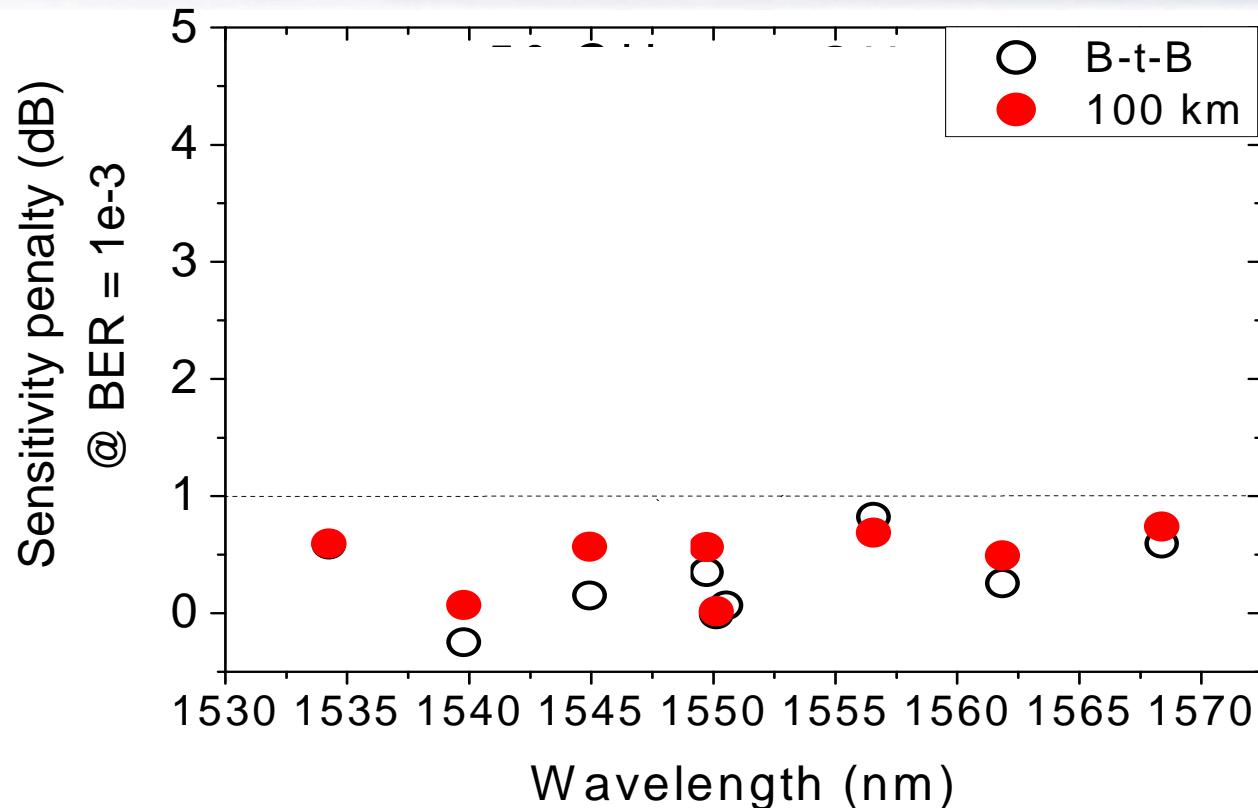


* Less than 2.5 dB of sensibility penalty after 25 km
Dynamic reconfiguration of client connections with joint flexibility in time and wavelength domains
 * Could be reduced by using more advanced coupling structure and new laser design (actual coupling loss: ~3dB)

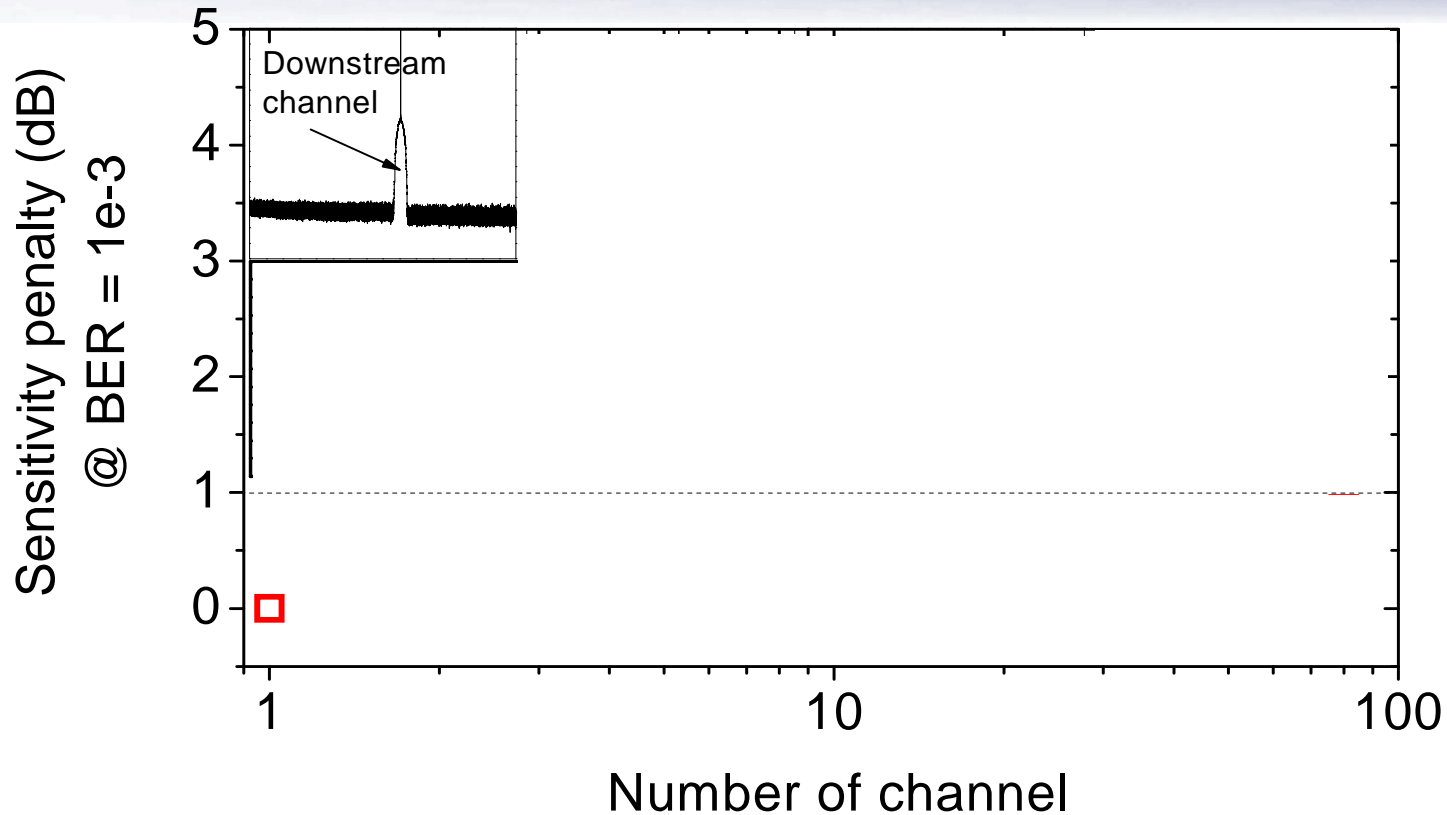
Coherent receiver using the hybrid laser as local oscillator



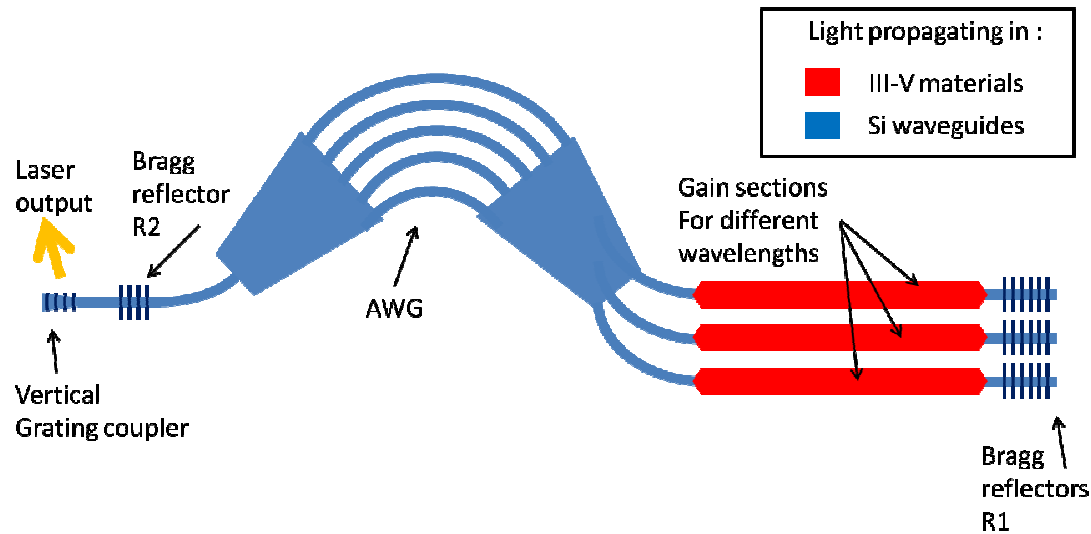
- ❖ Power sensitivity of -27 dBm in b-t-b @ BER = 10^{-3}
- ❖ No penalty compared to the reference laser (ECL)
- ❖ No further penalty after transmission
- ❖ Digital dispersion compensation in the receiver



- ❖ **Sensitivity penalties with respect to the ECL**
- ❖ **Less than 1 dB channel-to-channel sensitivity across the C-band**
- ❖ **Consecutive wavelengths on the 50-GHz ITU grid**

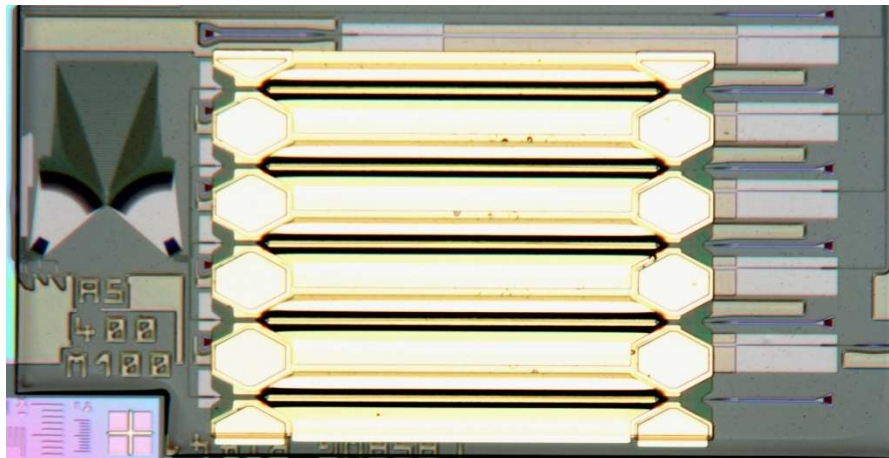


- ❖ **Number of neighboring channels up to a worst case of 80 (50 GHz)**
- ❖ **Possibility of filterless operation**



► Wavelength selectable source :

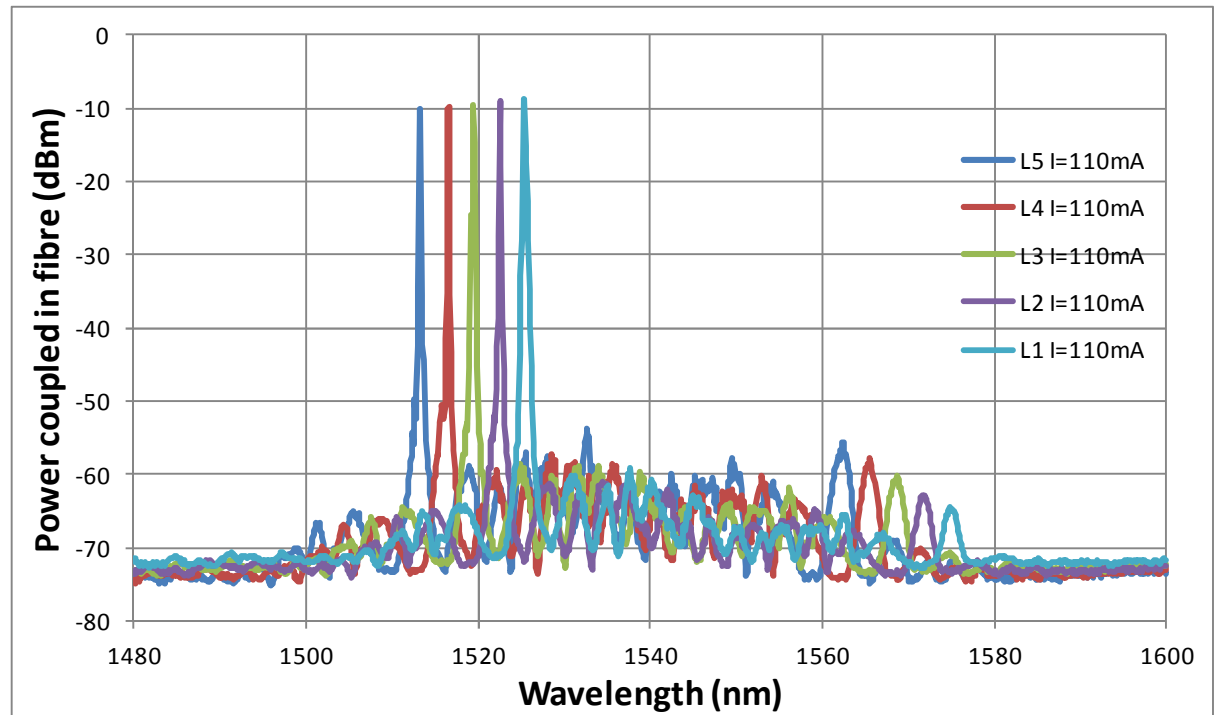
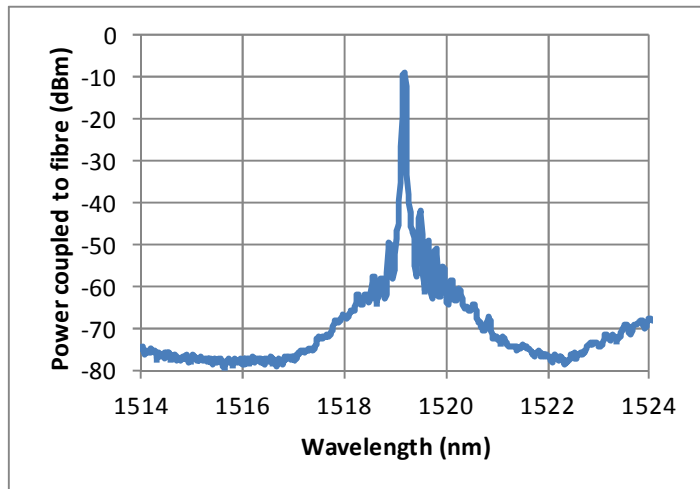
- Si AWG inside the laser cavity as a filter
- Broadband bragg reflectors for feedback
- Si AWG : 5 channels, 400GHz spacing
- Vertical bragg gratings for on wafer scale testing



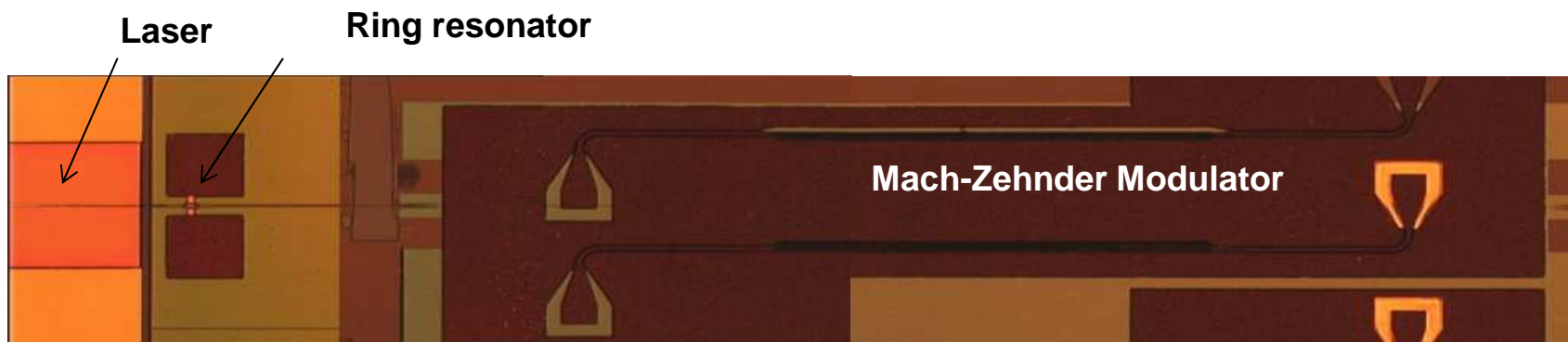
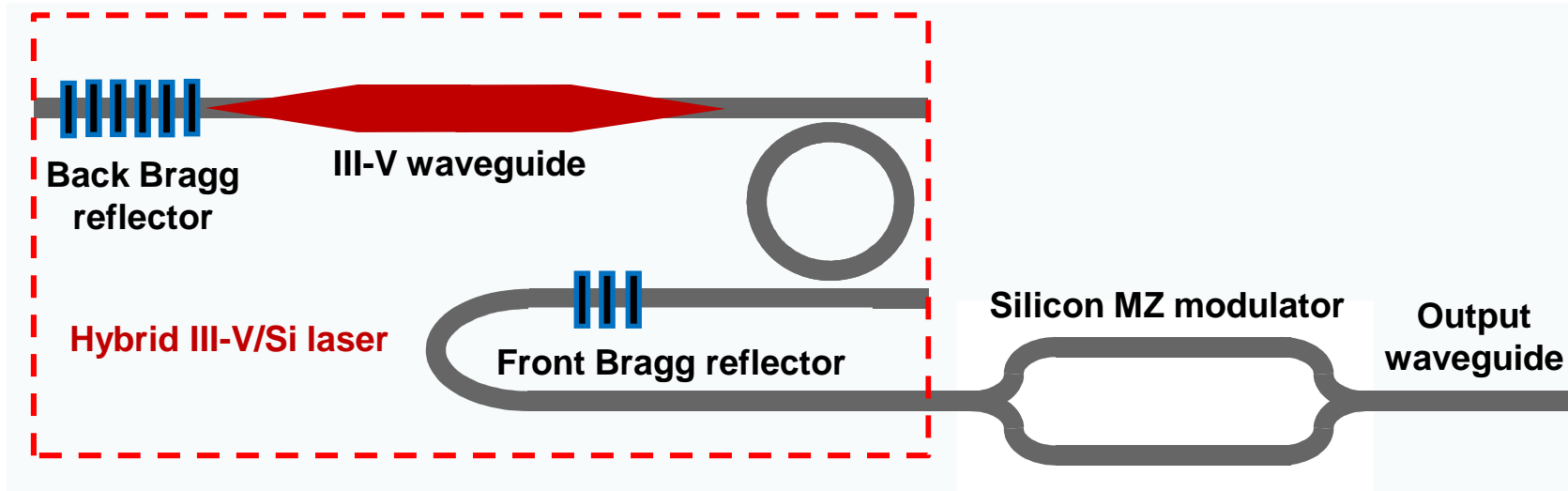
Simple wavelength tuning for access networks

Can also be used as multi-wavelength source

- Spectrum for each channel with 110mA injection
- Single mode operation with > 30 dB SMSR
- 390GHz spacing between channels

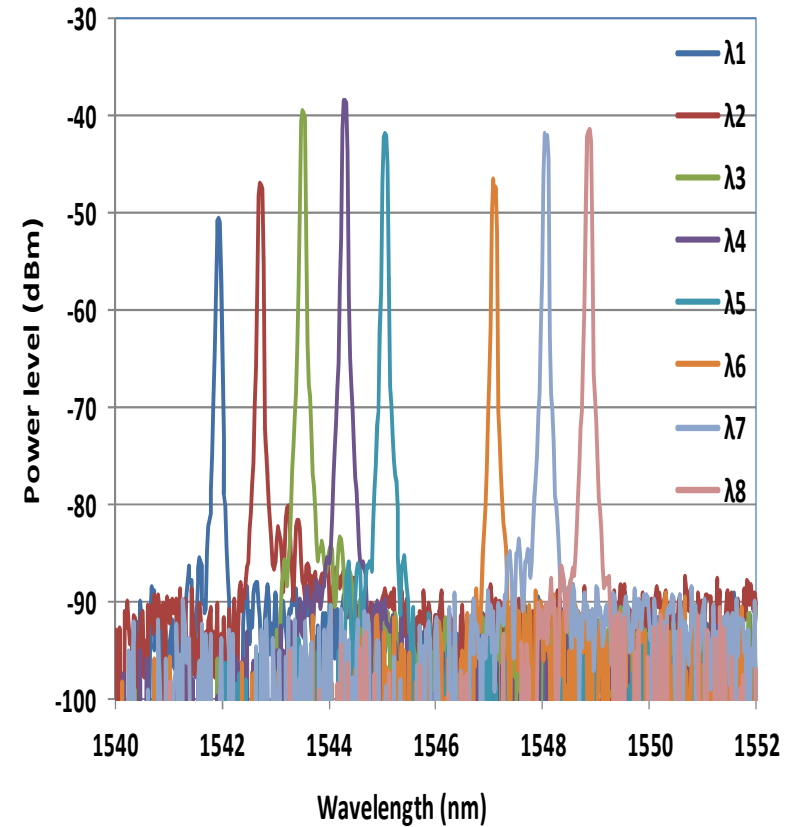
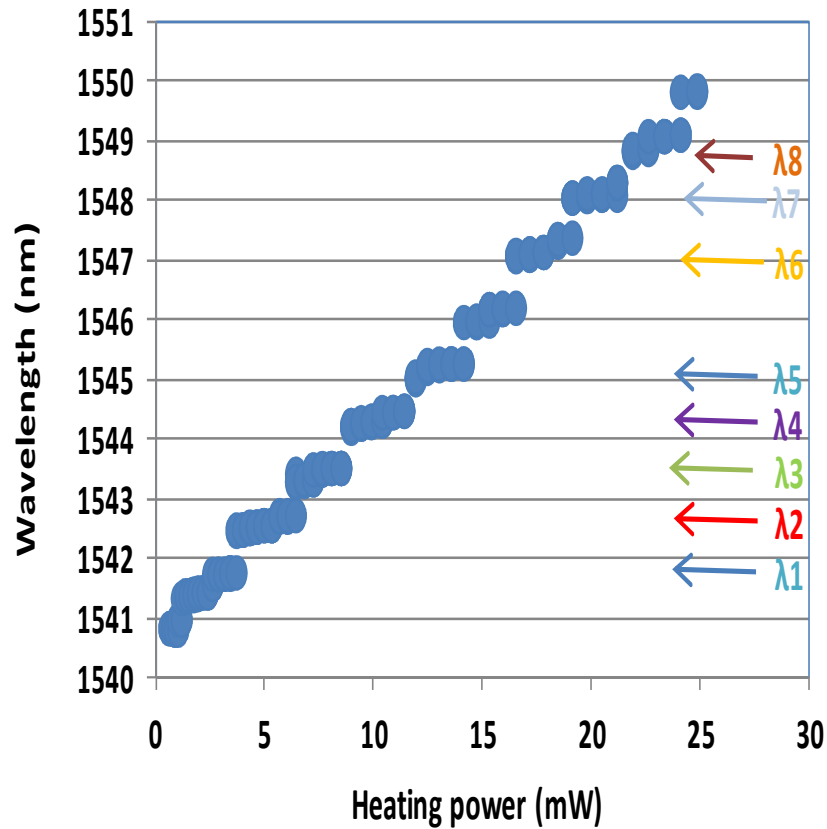


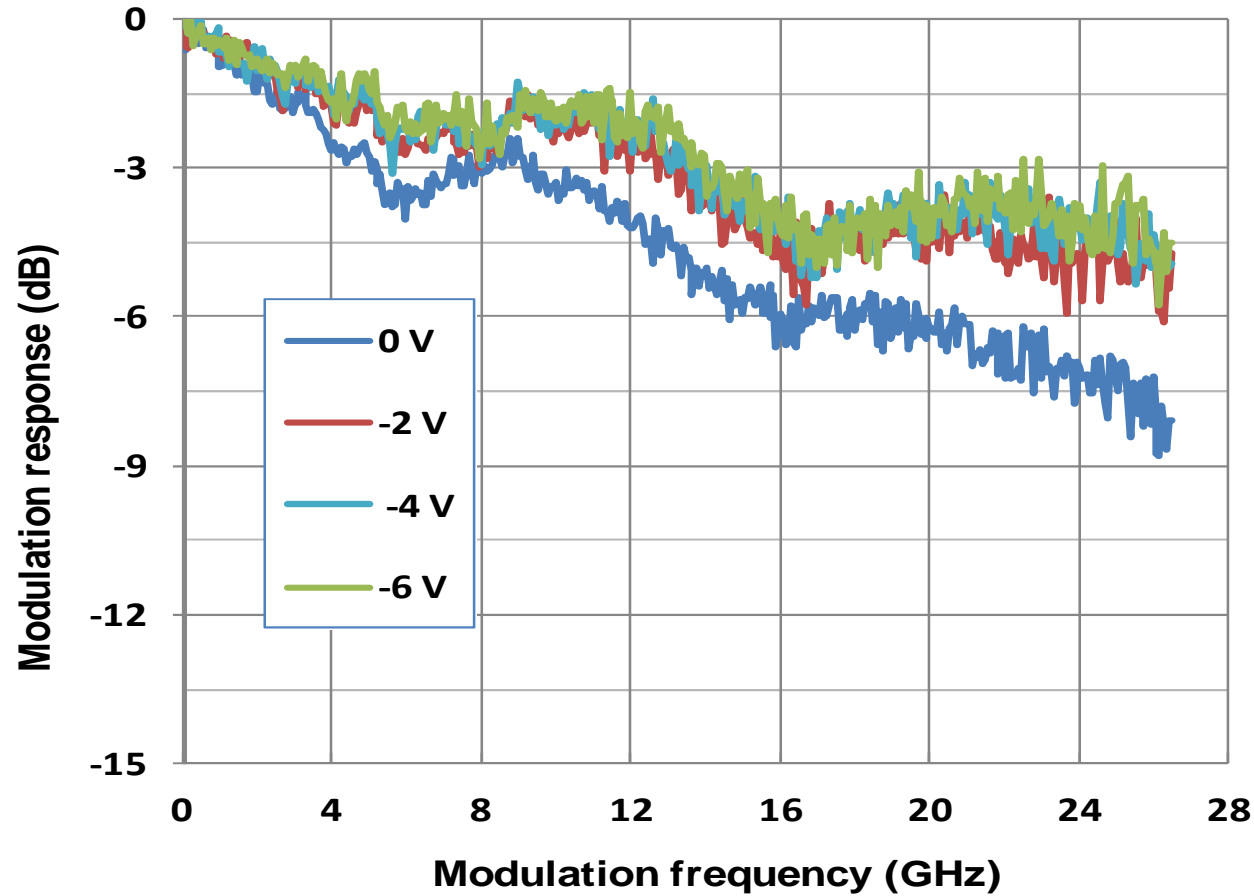
Spectrum for each channel



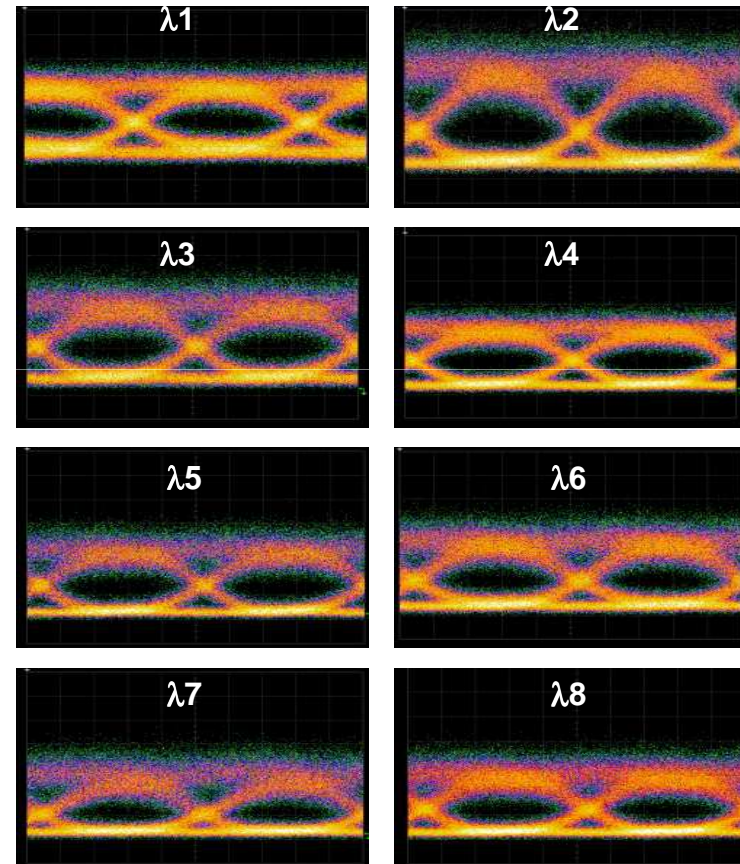
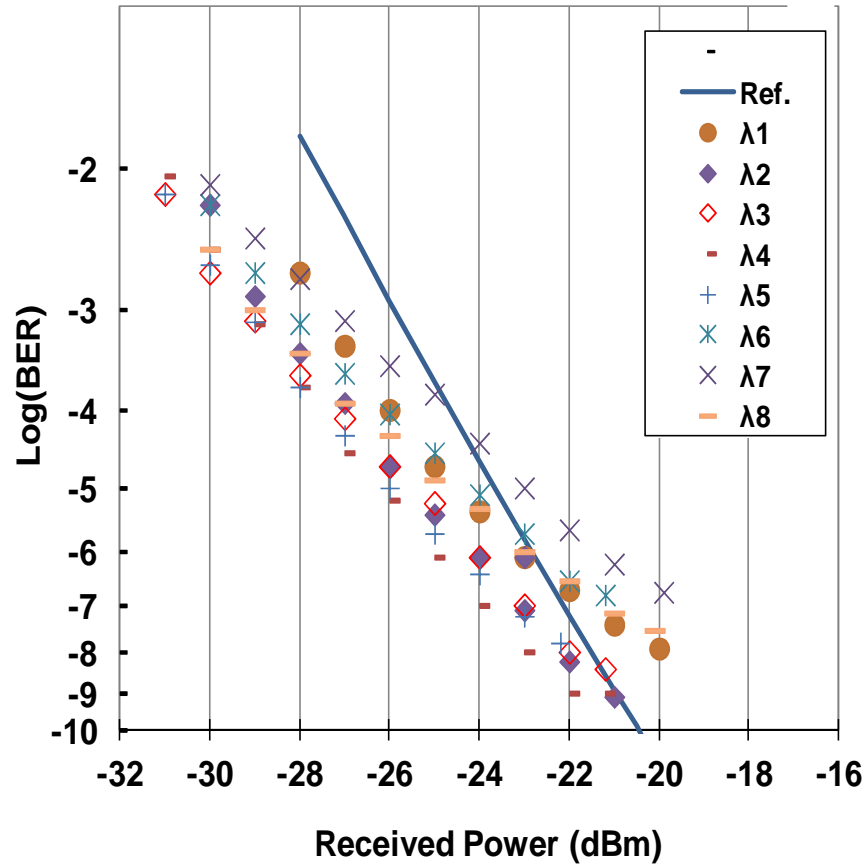
G. -H. Duan, et al., ECOC 2012

Wavelength tunability over 9 nm

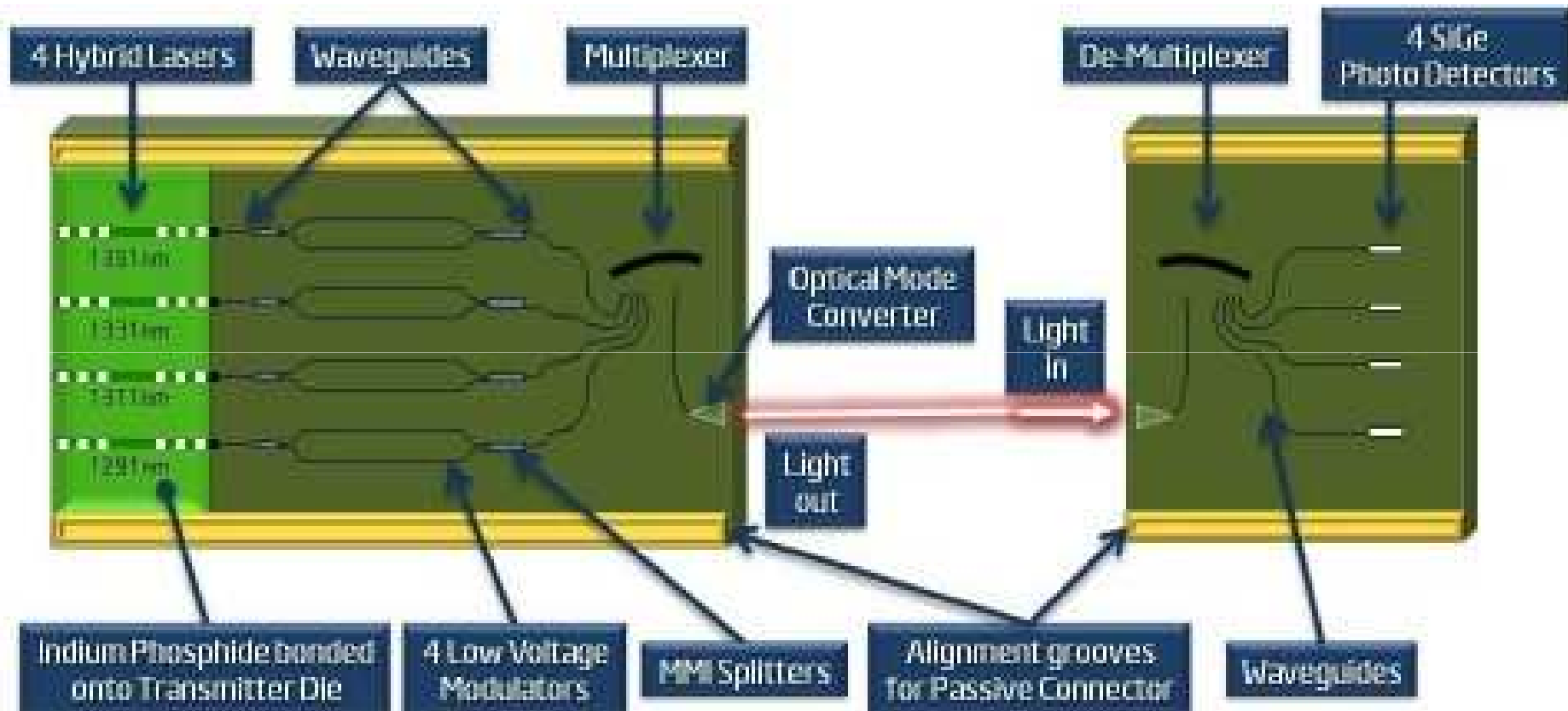




▪ 3 dB modulation bandwidth around 13 GHz

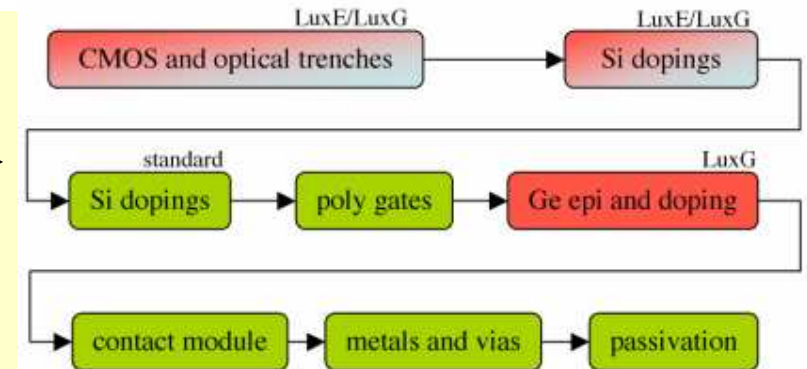


	III-V Lab		LETI	Intel/UCSB			Monolithic InP lasers	
Type	Si FP	Si RRs	Si DBR	Si DBR	Si DFB	Si DBR	DFB	SG DBR
Silicon waveguide thickness (nm)	400	440	500	500	500	500	/	/
I _{th} (mA) at 20°C	30	21	40	45	25	65	< 20	< 20
η (mW/mA) at 20°C	0.1	0.1	0.1	0.1	0.05	0.15	> 0.25	> 0.25
P _{max} (mW) at 20°C	18	10	14	30	5.4	11	30	20
SMSR (dB)	/	45	>20	/	40	40	40	35
Tunability (nm)	/	45	/	/	/	/	/	40
T° max operation	60°C	60°C	60°C	90°C	50°C	45°C	90°C	90°C
Wavelength (μm)	1.55	1.55	1.55	1.3	1.55	1.55	1.3-1.55	1.55



Luxtera technology for transceiver

- Freescale SC Hip7 0.13 μ m SOI CMOS process
- Customized SOI & CMOS 130nm technology
- Proprietary library for electronic design
 - Flip chip laser die bonding
 - Si lateral depletion modulator \rightarrow 10Gb/s
 - Ge photodetectors \rightarrow 20GHz
 - Surface holographic gratings fiber coupling
 - 4x28 Gb/s using 4 parallel links

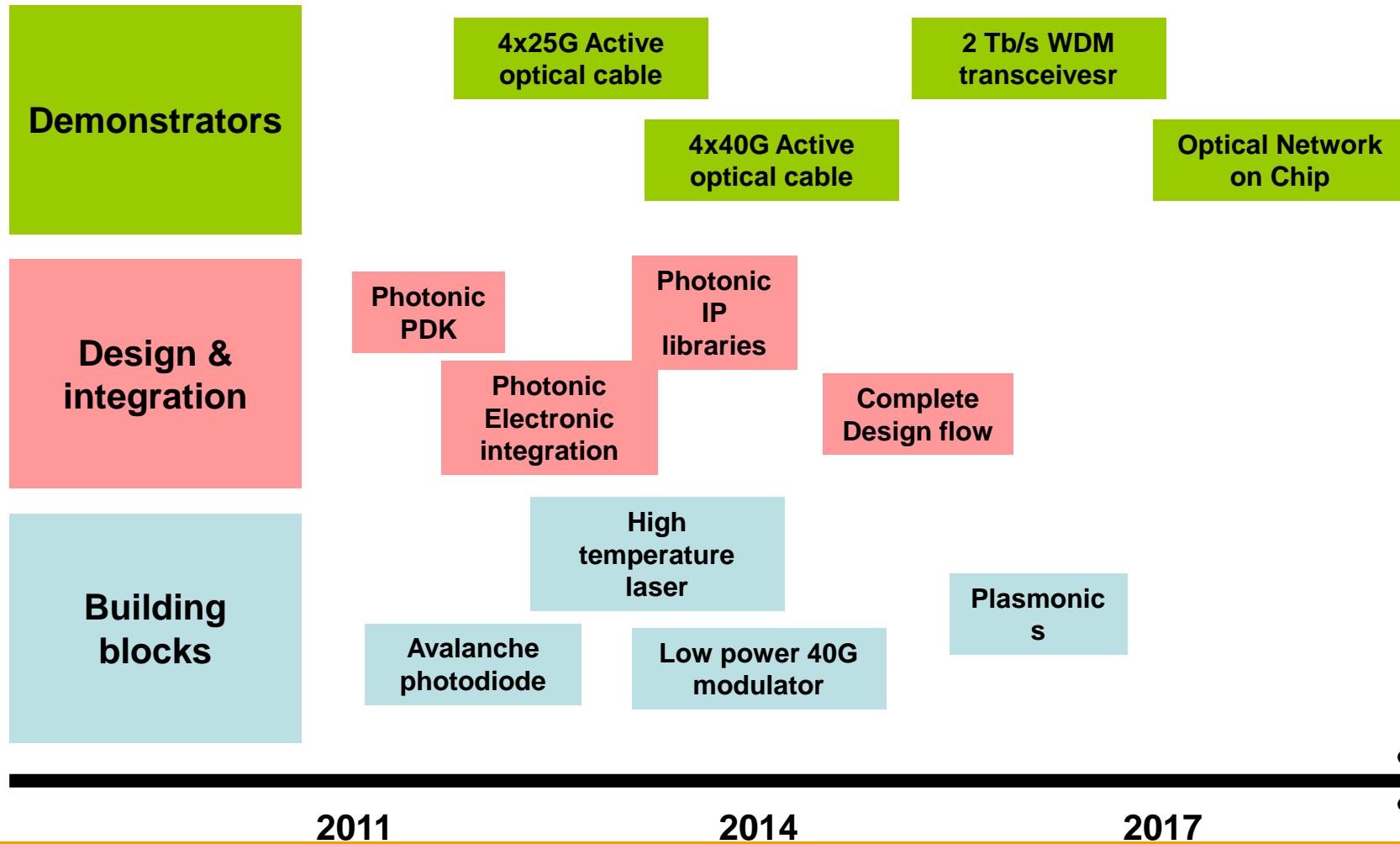


Luxtera and STMicroelectronics to Enable High-Volume Silicon Photonics Solutions

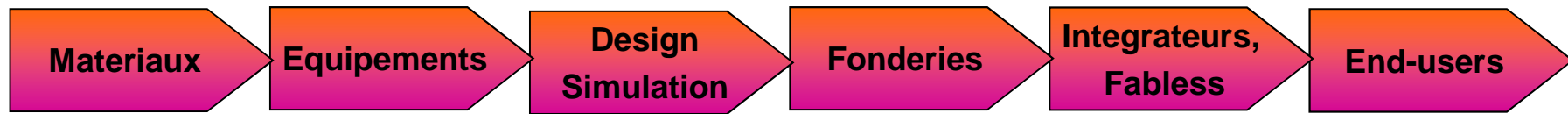
Collaboration between two leading companies will bring silicon photonics into mainstream markets

March 1st, 2012





La chaine de la valeur en photonique silicium



<p>Soitec IQE</p>	<p>Replisaurus/SET EVG Agilent Cascade</p>	<p>PhoeniX Mentor Graphics Cadence Dolphin integration ARM</p>	<p>ST</p> <p>ALTIS LFoundry Globalfoundries</p> <p>Intel IBM</p>	<p>ST</p> <p>3S Photonics OCLARO DAS Photonics Caliopa</p> <p>Intel, IBM, HP, Oracle Finisar, PMC-Sierra Altera Luxtera, Kotura, Genalyte Aurrion Skorpious</p>	<p>Bull Tyco Electronics IBM Alcatel-Lucent Thales FCI Radiall Ericsson Nokia</p> <p>Oracle Google Cisco</p>
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New start-ups?

▶ **European projects:**

- HELIOS, Plat4M, Fabulous

▶ **French national projects:**

- ANR MICROS (coherent receiver)
- ANR SILVER (transceiver for access networks)

▶ **III-V Lab:**

- C. Jany, A. Le Liepvre, M. Lamponi, A. Accard, F. Poingt, D. Make, F. Lelarge, G. Levaufre, N. Girard

▶ **CEA:**

- S. Messaoudene, D. Bordel, and J.-M. Fedeli, C Kopp, B. Ben Bakir, L. Fulbert

▶ **Photonics Research Group, INTEC, Ghent University-IMEC**

- S. Keyvaninia, G. Roelkens, D. Van Thourhout

▶ **School of Electronics and Computer Science, University of Southampton**

- D. J. Thomson, F. Y. Gardes and G. T. Reed